Magic Maintainer's Manual #2: The Technology File

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(Updated by others, too.)

This manual corresponds to Magic version 7.4 and technology format 30

Tutorials to read first:

Magic Tutorial #1: Getting Started Magic Tutorial #2: Basic Painting and Selection Magic Tutorial #6: Design-Rule Checking Magic Tutorial #8: Circuit Extraction Magic Tutorial #9: Format Conversion for CIF and Calma

You should also read at least the first, and probably all four, of the papers on Magic that appeared in the *ACM IEEE 21st Design Automation Conference*, and the paper "Magic's Circuit Extractor", which appeared in the *ACM IEEE 22nd Design Automation Conference*. The overview paper from the DAC was also reprinted in *IEEE Design and Test* magazine in the February 1985 issue. The circuit extractor paper also appeared in the February 1986 issue of *IEEE Design and Test* magazine. **Commands introduced in this manual:**

path tech *watch

Macros introduced in this manual:

(None)

Changes since Magic version 7.2:

- Support for stacked contacts.
- "variants" option for the cifinput, cifoutput, and extract sections, allowing an efficient description of different styles having minor variations.
- Supports names for layer drawing styles in addition to the usual numbers.
- Section name **images** duplicates the **contacts** section, allowing a less-restrictive definition of images that exist, like contacts, on multiple planes.
- Support for multi-line technology descriptions.
- "include" statement to divide technology files into parts.
- "alias" statements to replace the original cpp-style macros
- Support for *angstroms* in the scalefactor line of cifinput and cifoutput.
- Additional DRC types "surround", "overhang", and "rect_only".
- Additional cifoutput operators "slots" and "bloat-all".
- Additional cifoutput statement "render" for 3-D information
- Asterisk syntax for layers that expands to the layer and all of the contacts containing that layer as a residue.
- The technology file syntax for the PNM format was changed in magic 7.3.56, and the **plot pnm** command will use a default style derived from the layout styles if no section is present in the technology file.

Changes since Magic version 6.5:

- Moved technology format from the filename to the "tech" section
- Added subdirectory searching to the path search for technology files.
- Support for technology file re-loading after Magic starts up, and support for re-loading of individual sections of the technology file.
- Scalefactors can now be any number whatsoever, for both CIF and GDS. For example, a scalefactor of 6.5 corresponds to a 0.13 micron process.
- A parameter *nanometers* has been added to the scalefactor specification for both cifinput and cifoutput sections. This parameter declares that all numbers in the style description are in nanometers instead of centimicrons.
- The *calmaonly* parameter to the scalefactor specification is deprecated (ignored if found).
- The scale reducer parameter is deprecated (generated automatically, and ignored if found in the techfile).

- The magic grid spacing is no longer assumed to be equal to the process lambda. It may be rescaled with the "scalegrid" command, and CIF and Calma reads may alter the value of magic units per lambda.
- Support for PNM and PostScript graphics in the "plot" section.
- Full support for bipolar junction transistors, capacitors, and resistors with the "extract" section keyword "device"
- Support for three-dimensional modeling and geometry extraction
- Support for the DRC widespacing rule
- Handling of contacts in the extraction section is capable of matching the CIF output section by specifying border, size, and spacing.

1 Introduction

Magic is a technology-independent layout editor. All technology-specific information comes from a *technology file*. This file includes such information as layer types used, electrical connectivity between types, design rules, rules for mask generation, and rules for extracting netlists for circuit simulation.

This manual describes the use, contents, and syntax of Magic's technology file format, and gives hints for building a new one or (more typically) rewriting an existing one for a new fabrication process. References to specific files in the Magic distribution assume that your current working directory is the Magic source top-level directory.

2 Downloads and Installation

Typically, there is a different technology file for each fabrication process supported by Magic. Scalable technologies, which are (within limits) independent of feature size, will typically have one technology file for all processes supporting the same set of lambda-based (scalable) DRC rules. That said, modern technologies (post-1980's, more or less) tend to be more restrictive in their design rules, and consequently not scalable. This is particularly true of processes which push the envelope on feature sizes.

The Magic source distribution is packaged with a "standard" set of scalable SCMOS rules, which is the technology loaded by default. Default settings are for 1 μ m technology, which is out of date. However, the variety and availability of processes means that the "definitive" set of technology files is prohibitively large to be included with the Magic source. In addition, process refinements generally require technology file updates on a regular basis. Because of this, the basic collection of technology files is handled by the MOSIS foundation, not by the Magic development team. This collection represents all processes which are available for fabrication through the MOSIS foundation. Most other vendors have proprietary process specifications, requiring tool maintainers to write their own technology files or modify an existing one to match the proprietary process.

The standard technology file set can be downloaded from an FTP server at the MOSIS foundation. These files are regularly updated, but there is usually a symbolic link called "current" to the most recent stable revision. The download URL is the following:

ftp://ftp.mosis.edu/pub/sondeen/magic/new/beta/current.tar.gz

Assuming that the install destination for magic is /usr/local, this file should be put either in /usr/local/lib/magic/sys or (preferably) in /usr/local/lib/magic/sys/current. Other destinations may be used, if the system search path is appropriately specified on startup (see Section 3, below).

The technology file collection is in tarred, gzipped format, and should be installed with the following commands:

cd /usr/local/lib/magic/sys/current
gunzip current.tar.gz
tar xf current.tar

Once unpacked, these files are ready to be used in Magic.

3 Command-Line Invocation

You can run Magic with a different technology by specifying the **-***Ttechfile* flag on the command line you use to start Magic, where *techfile* is the name of a file of the form *techname***.tech**, searched for in one of the following directories (listed by search order):

- 1. The current directory
- 2. The library directory /usr/local/lib/magic/sys
- 3. The library directory /usr/local/lib/magic/current

This search order is not fixed and can be altered by the command **path sys**, which may be redefined in the system or user **.magic** startup script file. In addition, the startup script may load a new techfile, regardless of what was specified on the command line, or may load a new techfile provided that one has not been specified on the command line (the **-nooverride** option. The **-noprompt** switch causes the technology to be loaded without first prompting the user for confirmation.

tech load filename -noprompt [-nooverride]

4 Technology File Format Overview

A technology file is organized into sections, each of which begins with a line containing a single keyword and ends with a line containing the single word **end**. If you examine one of the Magic technology files in the installation directory ${CAD_HOME}/lib/magic/sys/, e.g., scmos.tech, you can see that it contains the following sections:$

tech planes types styles contact compose connect cifoutput cifinput mzrouter drc extract wiring router plowing plot

These sections must appear in this order in all technology files. Every technology file must have all of the sections, although the sections need not have any lines between the section header and the **end** line.

Historically, technology files were written in a C-language context which was processed by the C preprocessor. This allows the use of C-language comments ("/* ...*/") and the use of preprocessing definitions ("#define ...") and conditionals ("#ifdef ...#endif"). The technology files were generated from a Makefile with the preprocessor constructs used to generate different sections of the technology file at different lambda scales. The decreasing use of scalable processes, however, has made this method largely obsolete, and the standard collection of technology files from MOSIS does not use them at all. Technology files are now written in their final form, not in preprocessed form. Information regarding preprocessor constructs is not included below, but can of course be obtained from the manual pages for the preprocessor itself (gcc or cpp). But also note that the use of C preprocessors for processing text files other than source code is now generally discouraged in favor of using a macro definition processors are almost universally despised, so many preprocessor functions have been written into the technology file syntax.

The default **scmos** set of technology files included with the Magic distribution is still processed via the C preprocessor. Preprocessed files have the extension "**.tech.in**". Technology files written specifically for Magic version 7.3 tend to make use of additional features of the technology file syntax that subsume most of the functions of the C preprocessor and M4 processor normally used to generate technology files.

Each section in a technology file consists of a series of lines. Each line consists of a series of words, separated by spaces or tabs. If a line ends with the character "\", the "\" is ignored and the following newline is treated as an ordinary blank. For example,

width allDiff 2 \

"Diffusion width must be at least 2"

is treated as though it had all appeared on a single line with no intervening "\". On the other hand, for the purposes of tracking errors in technology file input, the technology file parser treats

these as separate lines, so that when magic reports an error on a specific line of the technology file, it will agree with the line numbering of the editor used to edit the file.

Comments may be embedded in the technology file. Magic's technology file parser will ignore all text beginning with the character # through the end of the line.

The rest of this part of the manual will describe each of the technology file sections in turn.

5 Tech section

Magic stores the technology of a cell in the cell's file on disk. When reading a cell back in to Magic from disk, the cell's technology must match the name of the current technology, which appears as a single word in the **tech** section of the technology file. See Table 1 for an example.

tech
format 30
scmos
end

Table 1: Tech section

The name of the technology declared in the **tech** section is meaningful to Magic, whereas the name of the file itself is not. Typically the name of the file will be the same as the name of the technology, to avoid confusion, but this need not be the case.

Versions of magic prior to 7.2 embedded the format version of the technology in the file name, *e.g.*, **scmos.tech27**. The last format version to use this syntax, 27, is still accepted as a valid filename extension. Many technology files still use this notation, including (at the time of writing) the collection from MOSIS. Now the format is declared inside the **tech** section.

6 A short tutorial on "corner stitching"

The **planes**, **types**, and **contact** sections are used to define the layers used in the technology. Magic uses a data structure called *corner-stitching* to represent layouts. Corner-stitching represents mask information as a collection of non-overlapping rectangular *tiles*. Each tile has a type that corresponds to a single Magic layer. An individual corner-stitched data structure is referred to as a *plane*.

Magic allows you to see the corner-stitched planes it uses to store a layout. We'll use this facility to see how several corner-stitched planes are used to store the layers of a layout. Enter Magic to edit the cell **maint2a**. Type the command ***watch active demo**. You are now looking at the **active** plane. Each of the boxes outlined in black is a tile. (The arrows are *stitches*, but are unimportant to this discussion.) You can see that some tiles contain layers (polysilicon, ndiffusion, ndcontact, polycontact, and ntransistor), while others contain empty space. Corner-stitching is unusual in that it represents empty space explicitly. Each tile contains exactly one type of material, or space.

You have probably noticed that metall does not seem to have a tile associated with it, but instead appears right in the middle of a space tile. This is because metall is stored on a different

plane, the **metal1** plane. Type the command **:*watch metal1 demo**. Now you can see that there are metal1 tiles, but the polysilicon, diffusion, and transistor tiles have disappeared. The two contacts, polycontact and ndcontact, still appear to be tiles.

The reason Magic uses several planes to store mask information is that corner-stitching can only represent non-overlapping rectangles. If a layout were to consist of only a single layer, such as polysilicon, then only two types of tiles would be necessary: polysilicon and space. As more layers are added, overlaps can be represented by creating a special tile type for each kind of overlap area. For example, when polysilicon overlaps ndiffusion, the overlap area is marked with the tile type ntransistor.

Although some overlaps correspond to actual electrical constructs (e.g., transistors), other overlaps have little electrical significance. For example, metal1 can overlap polysilicon without changing the connectivity of the circuit or creating any new devices. The only consequence of the overlap is possibly a change in parasitic capacitance. To create new tile types for all possible overlapping combinations of metal1 with polysilicon, diffusion, transistors, etc. would be wasteful, since these new overlapping combinations would have no electrical significance.

Instead, Magic partitions the layers into separate planes. Layers whose overlaps have electrical significance must be stored in a single plane. For example, polysilicon, diffusion, and their overlaps (transistors) are all stored in the **active** plane. Metall does not interact with any of these tile types, so it is stored in its own plane, the **metall** plane. Similarly, in the scmos technology, metal2 doesn't interact with either metall or the active layers, so is stored in yet another plane, **metal2**.

Contacts between layers in one plane and layers in another are a special case and are represented on *both* planes. This explains why the pcontact and ndcontact tiles appeared on both the **active** plane and on the **metal1** plane. Later in this section, when the **contacts** section of the technology file is introduced, we'll see how to define contacts and the layers they connect.

7 Planes, types, and contact sections

The **planes** section of the technology file specifies how many planes will be used to store tiles in a given technology, and gives each plane a name. Each line in this section defines a plane by giving a comma-separated list of the names by which it is known. Any name may be used in referring to the plane in later sections, or in commands like the ***watch** command indicated in the tutorial above. Table 2 gives the **planes** section from the scmos technology file.

planes
well,w
active, diffusion, polysilicon, a
metal1,m1
metal2,m2
oxide,ox
end

Table 2: Planes section

Magic uses a number other planes internally. The **subcell** plane is used for storing cell instances rather than storing mask layers. The **designRuleCheck** and **designRuleError** planes are used by

the design rule checker to store areas to be re-verified, and areas containing design rule violations, respectively. Finally, the **mhint**, **fhint**, and **rhint** planes are used for by the interactive router (the **iroute** command) for designer-specified graphic hints.

There is a limit on the maximum number of planes in a technology, including the internal planes. This limit is currently 64. To increase the limit, it is necessary to change **MAXPLANES** in the file **database/database.h.in** and then recompile all of Magic as described in "Maintainer's Manual #1". Each additional plane involves additional storage space in every cell and some additional processing time for searches, so we recommend that you keep the number of planes as small as you can do cleanly.

The **types** section identifies the technology-specific tile types used by Magic. Table 3 gives this section for the scmos technology file. Each line in this section is of the following form:

plane names

Each type defined in this section is allowed to appear on exactly one of the planes defined in the **planes** section, namely that given by the *plane* field above. For contacts types such as **pcontact**, the plane listed is considered to be the contact's *home* plane; in Magic 7.3 this is a largely irrelevant distinction. However, it is preferable to maintain a standard of listing the lowest plane connected to a contact as it's "home plane" (as they appear in the table).

tumor	
types	
active	polysilicon,red,poly,p
active	ndiffusion,green,ndiff
active	pdiffusion,brown,pdiff
metal1	metal1,m1,blue
metal2	metal2,m2,purple
well	pwell,pw
well	nwell,nw
active	polycontact,pcontact,pc
active	ndcontact,ndc
active	pdcontact,pdc
metal1	m2contact,m2c,via,v
active	ntransistor,nfet
active	ptransistor, pfet
active	psubstratepcontact,ppcontact,ppcont,psc,ppc,pwc,pwcontact
active	nsubstratencontact,nncontact,nncont,nsc,nnc,nwc,nwcontact
active	psubstratepdiff,psd,ppdiff,ppd,pohmic
active	nsubstratendiff,nsd,nndiff,nnd,nohmic
metal2	pad
oxide	glass
end	

Table 3: Types section

The *names* field is a comma-separated list of names. The first name in the list is the "long" name for the type; it appears in the **.mag** file and whenever error messages involving that type are

printed. Any unique abbreviation of any of a type's names is sufficient to refer to that type, both from within the technology file and in any commands such as **paint** or **erase**.

Magic has certain built-in types as shown in Table 4. Empty space (**space**) is special in that it can appear on any plane. The types **error_p**, **error_s**, and **error_ps** record design rule violations. The types **checkpaint** and **checksubcell** record areas still to be design-rule checked. Types **magnet**, **fence**, and **rotate** are the types used by designers to indicate hints for the irouter.

Tile type	Plane
space	all
error_p, EP	designRuleError
error_s, ES	designRuleError
error_ps, EPS	designRuleError
checkpaint, CP	designRuleCheck
checksubcell, CS	designRuleCheck
magnet, mag	mhint
fence, f	fhint
rotate, r	rhint

Table 4: Built-in Magic types

There is a limit on the maximum number of types in a technology, including all the built-in types. Currently, the limit is 256 tile types. To increase the limit, you'll have to change the value of **TT_MAXTYPES** in the file **database/database.h.in** and then recompile all of Magic as described in "Maintainer's Manual #1". Because there are a number of tables whose size is determined by the square of **TT_MAXTYPES**, it is very expensive to increase **TT_MAXTYPES**. Magic version 7.2 greatly reduced the number of these tables, so the problem is not as bad as it once was. Most internal tables depend on a *bitmask* of types, the consequence of which is that the internal memory usage greatly increases whenever **TT_MAXTYPES** exceeds a factor of 32 (the size of an integer, on 32-bit systems). Magic version 7.3 further alleviates the problem by reducing the number of "derived" tile types that magic generates internally, so that the total number of types is not much larger than the number declared in the **types** section. Magic-7.4 only generates extra types for pairs of stackable contact types. For a typical process, the number of these derived stacked contact pairs is around 15 to 20.

The declaration of tile types may be followed by a block of alias declarations. This is similar to the "macro" definitions used by preprocessors, except that the definitions are not only significant to the technology file parser, but extend to the user as well. Thus the statement "**alias metalstack m1,m2,m3**" may be a convenient shorthand where metal layers 1, 2, and 3 appear simultaneously, but the end-user can type the command "**paint metalstack**" and get the expected result of all three metal layers painted. The **alias** statement has the additional function of allowing backward-compatibility for technology files making use of stackable contacts (see below) with older layouts, and cross-compatibility between similar technologies that may have slight differences in layer names.

The **contact** section lets Magic know which types are contacts, and the planes and component types to which they are connected.

Each line in the **contact** section begins with a tile type, *base*, which is thereby defined to be a contact. This type is also referred to as a contact's *base type*. The remainder of each line is a list of non-contact tile types that are connected by the contact. These tile types are referred to as the *residues* of the contact, and are the layers that would be present if there were no electrical connection (*i.e.*, no via hole). In Table 5, for example, the type **pcontact** is the base type of a contact connecting the residue layers **polysilicon** on the active plane with **metal1** on the metal1 plane.

contact			
pcontact	poly	metal1	
ndcontact	ndiff	metal1	
pdcontact	pdiff	metal1	
ppcontact	ppdiff	metal1	
nncontact	nndiff	metal1	
m2contact	metal2	metal1	
pad	metal1	metal2	glass
end			

Table 5: Contact section

In Magic-7.3 and above, any number of types can be connected, and those types may exist on any planes. It is the duty of the technology file developer to ensure that these connections make sense, especially if the planes are not contiguous. However, because Magic-7.3 handles stacked contacts explicitly, it is generally better to define contacts only between two adjacent planes, and use the **stackable** keyword (see below) to allow types to be stacked upon one another. The multiple-plane representation exists for backward compatibility with technology files written for versions of Magic prior to 7.3. Stackable contacts in older technology files take the form:

contact pc polysilicon metal1 contact m2c metal1 metal2 contact pm12c polysilicon metal1 metal2

In Magic version 7.3, the above line would be represented as:

contact pc polysilicon metal1 contact m2c metal1 metal2 stackable pc m2c pm12c

where the third line declares that contact types m2c and pc may be stacked together, and that type name "pm12c" is a valid alias for the combination of "pc" and "m2c".

Each contact has an *image* on all the planes it connects. Figure 1 depicts the situation graphically. In later sections of the technology file, it is sometimes useful to refer separately to the various images of contact. A special notation using a slash character ("/") is used for this. If a tile type *aaa/bbb* is specified in the technology file, this refers to the image of contact *aaa* on plane *bbb*. For example, **pcontact/metal1** refers to the image of the pcontact that lies on the metal1 plane, and **pcontact/active** refers to the image on the active plane, which is the same as **pcontact**.

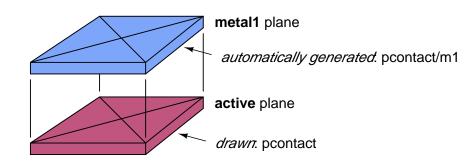


Figure 1: A different tile type is used to represent a contact on each plane that it connects. Here, a contact between poly on the **active** plane and metal1 on the **metal1** plane is stored as two tile types. One, **pcontact**, is specified in the technology file as residing on the **active** plane; the other is automatically-generated for the **metal1** plane.

8 Specifying Type-lists

In several places in the technology file you'll need to specify groups of tile types. For example, in the **connect** section you'll specify groups of tiles that are mutually connected. These are called *type-lists* and there are several ways to specify them. The simplest form for a type-list is a comma-separated list of tile types, for example

poly,ndiff,pcontact,ndc

The null list (no tiles at all) is indicated by zero, i.e.,

0

There must not be any spaces in the type-list. Type-lists may also use tildes ("~") to select all tiles but a specified set, and parentheses for grouping. For example,

~(pcontact,ndc)

selects all tile types but pcontact and ndc. When a contact name appears in a type-list, it selects *all* images of the contact unless a "/" is used to indicate a particular one. The example above will not select any of the images of pcontact or ndc. Slashes can also be used in conjunction with parentheses and tildes. For example,

~(pcontact,ndc)/active,metal1

selects all of the tile types on the active plane except for pcontact and ndc, and also selects metal1. Tildes have higher operator precedence than slashes, and commas have lowest precedence of all.

A special notation using the asterisk ("*") is a convenient way to abbreviate the common situation where a rule requires the inclusion of a tile type and also all contacts that define that tile type as one of their residue layers, a common occurrence. The notation

*metal1

expands to metall plus all of the contact types associated with metall, such as ndc, pdc, nsc, m2c, and so forth.

Note: in the CIF sections of the technology file, only simple comma-separated names are permitted; tildes and parentheses are not understood. However, everywhere else in the technology file the full generality can be used. The "*" notation for inclusion of contact residues may be present in any section.

9 Styles section

Magic can be run on several different types of graphical displays. Although it would have been possible to incorporate display-specific information into the technology file, a different technology file would have been required for each display type. Instead, the technology file gives one or more display-independent *styles* for each type that is to be displayed, and uses a per-display-type styles file to map to colors and stipplings specific to the display being used. The styles file is described in Magic Maintainer's Manual #3: "Styles and Colors", so we will not describe it further here.

Table 6 shows part of the **styles** section from the scmos technology file. The first line specifies the type of style file for use with this technology, which in this example is **mos**. Each subsequent line consists of a tile type and a style number (an integer between 1 and 63). The style number is nothing more than a reference between the technology file and the styles file. Notice that a given tile type can have several styles (e.g., pcontact uses styles #1, #20, and #32), and that a given style may be used to display several different tiles (e.g., style #2 is used in ndiff and ndcontact). If a tile type should not be displayed, it has no entry in the **styles** section.

It is no longer necessary to have one style per line, a restriction of format 27 and earlier. Multiple styles for a tile type can be placed on the same line, separated by spaces. Styles may be specified by number, or by the "long name" in the style file.

10 Compose section

The semantics of Magic's paint operation are defined by a collection of rules of the form, "given material *HAVE* on plane *PLANE*, if we paint *PAINT*, then we get Z", plus a similar set of rules for the erase operation. The default paint and erase rules are simple. Assume that we are given material *HAVE* on plane *PLANE*, and are painting or erasing material *PAINT*.

- 1. *You get what you paint.* If the home plane of *PAINT* is *PLANE*, or *PAINT* is space, you get *PAINT*; otherwise, nothing changes and you get *HAVE*.
- 2. *You can erase all or nothing.* Erasing space or *PAINT* from *PAINT* will give space; erasing anything else has no effect.

These rules apply for contacts as well. Painting the base type of a contact paints the base type on its home plane, and each image type on its home plane. Erasing the base type of a contact erases both the base type and the image types.

styles	
styles	
styletype mos	
poly	1
ndiff	2
pdiff	4
nfet	6
nfet	7
pfet	8
pfet	9
metal1	20
metal2	21
pcontact	1
pcontact	20
pcontact	32
ndcontact	2
ndcontact	20
ndcontact	32
pdcontact	4
pdcontact	20
pdcontact	32
m2contact	20
m2contact	21
m2contact	33
end	

Table 6: Part of the styles section

It is sometimes desirable for certain tile types to behave as though they were "composed" of other, more fundamental ones. For example, painting poly over ndiffusion in scmos produces ntransistor, instead of ndiffusion. Also, painting either poly or ndiffusion over ntransistor leaves ntransistor, erasing poly from ntransistor leaves ndiffusion, and erasing ndiffusion leaves poly. The semantics for ntransistor are a result of the following rule in the **compose** section of the scmos technology file:

compose ntransistor poly ndiff

Sometimes, not all of the "component" layers of a type are layers known to magic. As an example, in the **nmos** technology, there are two types of transistors: **enhancement-fet** and **depletion-fet**. Although both contain polysilicon and diffusion, depletion-fet can be thought of as also containing implant, which is not a tile type. So while we can't construct depletion-fet by painting poly and then diffusion, we'd still like it to behave as though it contained both materials. Painting poly or diffusion over a depletion-fet should not change it, and erasing either poly or diffusion should give the other. These semantics are the result of the following rule:

decompose dfet poly diff

The general syntax of both types of composition rules, compose and decompose, is:

compose type al bl a2 b2 ... **decompose** type al bl a2 b2 ...

The idea is that each of the pairs a1 b1, a2 b2, etc comprise *type*. In the case of a **compose** rule, painting any *a* atop its corresponding *b* will give *type*, as well as vice-versa. In both **compose** and **decompose** rules, erasing *a* from *type* gives *b*, erasing *b* from *type* gives *a*, and painting either *a* or *b* over *type* leaves *type* unchanged.

compose			
compose	nfet	poly	ndiff
compose	pfet	poly	pdiff
paint	pwell	nwell	nwell
paint	nwell	pwell	pwell
paint	pdc/active	pwell	ndc/active
paint	pdc/m1	pwell	ndc/m1
paint	pfet	pwell	nfet
paint	pdiff	pwell	ndiff
paint	nsd	pwell	psd
paint	nsc/active	pwell	psc/active
paint	nsc/m1	pwell	psc/m1
paint	ndc/active	nwell	pdc/active
paint	ndc/m1	nwell	pdc/m1
paint	nfet	nwell	pfet
paint	ndiff	nwell	pdiff
paint	psd	nwell	nsd
paint	psc/active	nwell	nsc/active
paint	psc/m1	nwell	nsc/m1
end			

Table 7: Compose section

Contacts are implicitly composed of their component types, so the result obtained when painting a type *PAINT* over a contact type *CONTACT* will by default depend only on the component types of *CONTACT*. If painting *PAINT* doesn't affect the component types of the contact, then it is considered not to affect the contact itself either. If painting *PAINT* does affect any of the component types, then the result is as though the contact had been replaced by its component types in the layout before type *PAINT* was painted. Similar rules hold for erasing.

A pcontact has component types poly and metal1. Since painting poly doesn't affect either poly or metal1, it doesn't affect a pcontact either. Painting ndiffusion does affect poly: it turns it into an ntransistor. Hence, painting ndiffusion over a pcontact breaks up the contact, leaving ntransistor on the active plane and metal1 on the metal1 plane.

The **compose** and **decompose** rules are normally sufficient to specify the desired semantics of painting or erasing. In unusual cases, however, it may be necessary to provide Magic with explicit **paint** or **erase** rules. For example, to specify that painting pwell over pdiffusion switches its type to ndiffusion, the technology file contains the rule:

paint pdiffusion pwell ndiffusion

This rule could not have been written as a **decompose** rule; erasing ndiffusion from pwell does not yield pdiffusion, nor does erasing pdiffusion from ndiffusion yield pwell. The general syntax for these explicit rules is:

Here, *have* is the type already present, on plane p if it is specified; otherwise, on the home plane of *have*. Type t is being painted or erased, and the result is type *result*. Table 7 gives the **compose** section for scmos.

It's easiest to think of the paint and erase rules as being built up in four passes. The first pass generates the default rules for all non-contact types, and the second pass replaces these as specified by the **compose**, **decompose**, etc. rules, also for non-contact types. At this point, the behavior of the component types of contacts has been completely determined, so the third pass can generate the default rules for all contact types, and the fourth pass can modify these as per any **compose**, etc. rules for contacts.

11 Connect section

For circuit extraction, routing, and some of the net-list operations, Magic needs to know what types are electrically connected. Magic's model of electrical connectivity used is based on signal propagation. Two types should be marked as connected if a signal will *always* pass between the two types, in either direction. For the most part, this will mean that all non-space types within a plane should be marked as connected. The exceptions to this rule are devices (transistors). A transistor should be considered electrically connected to adjacent polysilicon, but not to adjacent diffusion. This models the fact that polysilicon connects to the gate of the transistor, but that the transistor acts as a switch between the diffusion areas on either side of the channel of the transistor.

The lines in the **connect** section of a technology file, as shown in Table 8, each contain a pair of type-lists in the format described in Section 8. Each type in the first list connects to each type in the second list. This does not imply that the types in the first list are themselves connected to each other, or that the types in the second list are connected to each other.

Because connectivity is a symmetric relationship, only one of the two possible orders of two tile types need be specified. Tiles of the same type are always considered to be connected. Contacts are treated specially; they should be specified as connecting to material in all planes spanned by the contact. For example, pcontact is shown as connecting to several types in the active plane, as well as several types in the metal1 plane. The connectivity of a contact should usually be that of its component types, so pcontact should connect to everything connected to poly, and to everything connected to metal1.

connect				
#define allMetal2 m2,m2c/m2,pad/m2				
#define allMetal1 m1,m2c/m1,pc/m	m1,ndc/m1,pdc/m1,ppcont/m1,nncont/m1,pad/m1			
#define allPoly poly,pc/a,nfet,pfet				
allMetal2	allMetal2			
allMetal1	allMetal1			
allPoly	allPoly			
ndiff	ndc			
pdiff	pdc			
nwell,nnc,nsd	nwell,nnc,nsd			
pwell,ppc,psd	pwell,ppc,psd			
nnc	pdc			
ppc	ndc			
end				

 Table 8: Connect section

12 Cifoutput section

The layers stored by Magic do not always correspond to physical mask layers. For example, there is no physical layer corresponding to (the scmos technology file layer) ntransistor; instead, the actual circuit must be built up by overlapping poly and diffusion over pwell. When writing CIF (Caltech Intermediate Form) or Calma GDS-II files, Magic generates the actual geometries that will appear on the masks used to fabricate the circuit. The **cifoutput** section of the technology file describes how to generate mask layers from Magic's abstract layers.

12.1 CIF and GDS styles

From the 1990's, the CIF format has largely been replaced by the GDS format. However, they describe the same layout geometry, and the formats are similar enough that magic makes use of the CIF generation code as the basis for the GDS write routines. The technology file also uses CIF layer declarations as the basis for GDS output. So even a technology file that only expects to generate GDS output needs a "**cifoutput**" section declaring CIF layer names. If only GDS output is required, these names may be longer and therefore more descriptive than allowed by CIF format syntax.

The technology file can contain several different specifications of how to generate CIF. Each of these is called a CIF *style*. Different styles may be used for fabrication at different feature sizes, or for totally different purposes. For example, some of the Magic technology files contain a style "plot" that generates CIF pseudo-layers that have exactly the same shapes as the Magic layers. This style is used for generating plots that look just like what appears on the color display; it makes no sense for fabrication. Lines of the form

style name

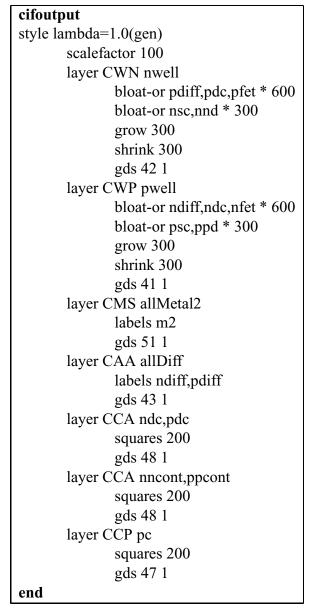


Table 9: Part of the **cifoutput** section for style lambda=1.0(gen) only.

are used to end the description of the previous style and start the description of a new style. The Magic command **:cif ostyle** *name* is typed by users to change the current style used for output. The first style in the technology file is used by default for CIF output if the designer doesn't issue a **:cif style** command. If the first line of the **cifoutput** section isn't a **style** line, then Magic uses an initial style name of **default**.

12.2 Scaling

Each style must contain a line of the form

scalefactor scale [nanometers|angstroms]

that tells how to scale Magic coordinates into CIF coordinates. The argument *scale* indicates how many hundredths of a micron correspond to one Magic unit. *scale* may be any number, including decimals. However, all units in the style description must be integer. Because deep submicron processes may require CIF operations in units of less than one centimicron, the optional parameter **nanometers** declares that all units (including the *scale* parameter) are measured in units of nanometers. Likewise, the units may all be specified in **angstroms**. However unlikely the dimensions may seem, the problem is that magic needs to place some objects, like contacts, on half-lambda positions to ensure correct overlap of contact cuts between subcells. A feature size such as, for example, 45 nanometers, has a half-lambda value of 22.5 nanometers. Since this is not an integer, magic will complain about this scalefactor. This is true even if the process doesn't *allow* sub-nanometer coordinates, and magic uses the *squares-grid* statement to enforce this restriction. In such a case, it is necessary to declare a scalefactor of 450 angstroms rather than 45 nanometers.

Versions of *magic* prior to 7.1 allowed an optional second (integer) parameter, *reducer*, or the keyword **calmaonly**. The use of *reducer* is integral to CIF output, which uses the value to ensure that output values are reduced to the smallest common denominator. For example, if all CIF values are divisible by 100, then the reducer is set to 100 and all output values are divided by the same factor, thus reducing the size of the CIF output file. Now the reducer is calculated automatically, avoiding any problems resulting from an incorrectly specified reducer value, and any value found after *scale* is ignored. The **calmaonly** keyword specified that the *scale* was an odd integer. This limitation has been removed, so any such keyword is ignored, and correct output may be generated for either CIF or Calma at all output scales.

In addition to specifying a scale factor, each style can specify the size in which chunks will be processed when generating CIF hierarchically. This is particularly important when the average design size is much larger than the maximum bloat or shrink (e.g, more than 3 orders of magnitude difference). The step size is specified by a line of the following form:

stepsize stepsize

where *stepsize* is in Magic units. For example, if you plan to generate CIF for designs that will typically be 100,000 Magic units on a side, it might make sense for *stepsize* to be 10000 or more.

12.3 Layer descriptions

The main body of information for each CIF style is a set of layer descriptions. Each layer description consists of one or more *operations* describing how to generate the CIF for a single layer. The first line of each description is one of

layer name [layers]

or

templayer name [layers]

These statements are identical, except that templayers are not output in the CIF file. They are used only to build up intermediate results used in generating the "real" layers. In each case, *name* is the CIF name to be used for the layer. If *layers* is specified, it consists of a comma-separated

list of Magic layers and previously-defined CIF layers in this style; these layers form the initial contents of the new CIF layer (note: the layer lists in this section are less general than what was described in Section 8; tildes and parentheses are not allowed). If *layers* is not specified, then the new CIF layer is initially empty. The following statements are used to modify the contents of a CIF layer before it is output.

After the **layer** or **templayer** statement come several statements specifying geometrical operations to apply in building the CIF layer. Each statement takes the current contents of the layer, applies some operation to it, and produces the new contents of the layer. The last geometrical operation for the layer determines what is actually output in the CIF file. The most common geometrical operations are:

> or layers and layers and-not layers grow amount shrink amount bloat-or layers layers2 amount layers2 amount... squares size squares border size separation

Some more obscure operations are:

grow-grid amount bloat-max layers layers2 amount layers2 amount . . . bloat-min layers layers2 amount layers2 amount . . . bloat-all layers layers2 squares-grid border size separation x y slots border size separation slots border size separation border_long slots border size separation border_long size_long sep_long [offset]] bbox [top]

The operation **or** takes all the *layers* (which may be either Magic layers or previously-defined CIF layers), and or's them with the material already in the CIF layer. The operation **and** is similar to **or**, except that it and's the layers with the material in the CIF layer (in other words, any CIF material that doesn't lie under material in *layers* is removed from the CIF layer). **And-not** finds all areas covered by *layers* and erases current CIF material from those areas. **Grow** and **shrink** will uniformly grow or shrink the current CIF layer by *amount* units, where *amount* is specified in CIF units, not Magic units. The **squares-grid** operator grows layers non-uniformly to snap to the grid spacing indicated by *amount*. This can be used to ensure that features fall on a required minimum grid.

The three "bloat" operations **bloat-or**, **bloat-min**, and **bloat-max**, provide selective forms of growing. In these statements, all the layers must be Magic layers. Each operation examines all the tiles in *layers*, and grows the tiles by a different distance on each side, depending on the rest of the line. Each pair *layers2 amount* specifies some tile types and a distance (in CIF units). Where

a tile of type *layers* abuts a tile of type *layers2*, the first tile is grown on that side by *amount*. The result is or'ed with the current contents of the CIF plane. The layer "*" may be used as *layers2* to indicate all tile types. Where tiles only have a single type of neighbor on each side, all three forms of **bloat** are identical. Where the neighbors are different, the three forms are slightly different, as illustrated in Figure 12.3. Note: all the layers specified in any given **bloat** operation must lie on a single Magic plane. For **bloat-or** all distances must be positive. In **bloat-max** and **bloat-min** the distances may be negative to provide a selective form of shrinking.

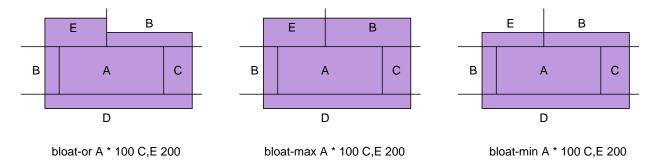


Figure 2: The three different forms of **bloat** behave slightly differently when two different bloat distances apply along the same side of a tile. In each of the above examples, the CIF that would be generated is shown in bold outline. If **bloat-or** is specified, a jagged edge may be generated, as on the left. If **bloat-max** is used, the largest bloat distance for each side is applied uniformly to the side, as in the center. If **bloat-min** is used, the smallest bloat distance for each side is applied uniformly to the side, as on the right.

In retrospect, it's not clear that **bloat-max** and **bloat-min** are very useful operations. The problem is that they operate on tiles, not regions. This can cause unexpected behavior on concave regions. For example, if the region being bloated is in the shape of a "T", a single bloat factor will be applied to the underside of the horizontal bar. If you use **bloat-max** or **bloat-min**, you should probably specify design-rules that require the shapes being bloated to be convex.

The fourth bloat operation **bloat-all** takes all tiles of types *layers*, and grows to include all neighboring tiles of types *layers2*. This is very useful to generate marker layers or implant layers for specific devices, where the marker or implant must cover both the device and its contacts. Take the material of the device and use **bloat-all** to expand into the contact areas.

An important geometric operation for creating contact cuts is **squares**. It examines each tile on the CIF plane, and replaces that tile with one or more squares of material. Each square is *size* CIF units across, and squares are separated by *separation* units. A border of at least *border* units is left around the edge of the original tile, if possible. This operation is used to generate contact vias, as in Figure 3. If only one argument is given in the **squares** statement, then *separation* defaults to *size* and *border* defaults to *size*/2. If a tile doesn't hold an integral number of squares, extra space is left around the edges of the tile and the squares are centered in the tile. If the tile is so small that not even a single square can fit and still leave enough border, then the border is reduced. If a square won't fit in the tile, even with no border, then no material is generated. The **squares** operation must be used with some care, in conjunction with the design rules. For example, if there are several adjacent skinny tiles, there may not be enough room in any of the tiles for a square, so no material will be generated at all. Whenever you use the **squares** operator, you should use design rules to prohibit adjacent contact tiles, and you should always use the **no_overlap** rule to prevent unpleasant hierarchical interactions. The problems with hierarchy are discussed in Section 12.6 below, and design rules are discussed in Section 15.

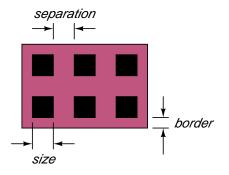


Figure 3: The **squares** operator chops each tile up into squares, as determined by the *border*, *size*, and *separation* parameters. In the example, the bold lines show the CIF that would be generated by a **squares** operation. The squares of material are always centered so that the borders on opposite sides are the same.

The squares-grid operator is similar to squares and takes the same arguments, except for the additional optional x and y offsets (which default to 1). Where the squares operator places contacts on the half-lambda grid, the squares-grid operator places contacts on an integer grid of x and y. This is helpful where manufacturing grid limitations do not allow half-lambda coordinates. However, it is necessary then to enforce a "no-overlap" rule for contacts in the DRC section to prevent incorrect contacts cuts from being generated in overlapping subcells. The squares-grid operator can also be used with x and y values to generate fill geometry, or to generate offset contact cut arrays for pad vias.

The **slots** operator is similar to **squares** operator, but as the name implies, the resulting shapes generated are rectangular, not (necessarily) square. Slots are generated inside individual tiles, like the squares operator, so each slots operation is separately oriented relative to the tile's long and short edges. Separate border, size, and separation values can be specified for the short and long dimensions of the tile. This operator can be used in a number of situations:

- 1. Generate square contact cuts with different border requirements on the short and long sides, as required for a number of deep submicron processes like 90 nanometer.
- 2. Automatically generate slots in large metal areas, which most processes require. Note, however, that it is impossible to correctly generate all slots, so this cannot completely replace the widespacing DRC rule.
- 3. Generate slot contacts.
- 4. Generate fill geometry.
- 5. Generate marker layers for resitors that abut the position of contacts, a generally-accepted way to define a resistor area boundary.

Note that the **slots** operator comes in three different forms with different numbers of arguments. With only three arguments (short side description only), the **slots** operator creates stripes that extend to the edge of the tile. With four arguments (short side description plus long side border dimension only), the **slots** operator create stripes that extend to the edge of the tile, with an appropriate border spacing at each end. In these two cases, the slots have variable length that is set by the size of the tile. In the final form, all short and long side dimensions are declared. The generated slots are of fixed size, and like the **squares** operator, their positions will be adjusted to center them on the tile. The *offset* is intended to let each row of slots be offset from the previous one by a fixed amount, but is currently unimplemented and has no effect.

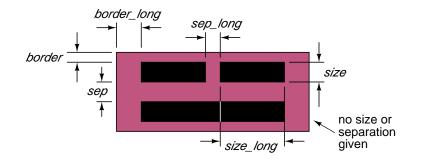


Figure 4: The slots operator chops each tile up into rectangles.

The **bbox** operator generates a single rectangle that encompasses the bounding box of the cell. This is useful for the occasional process that requires marker or implant layers covering an entire design. The variant **bbox top** will generate a rectangle encompassing the bounding box of the cell, but will only do so for the top-level cell of the design.

12.4 Labels

There is an additional statement permitted in the **cifoutput** section as part of a layer description:

labels Magiclayers

This statement tells Magic that labels attached to Magic layers *Magiclayers* are to be associated with the current CIF layer. Each Magic layer should only appear in one such statement for any given CIF style. If a Magic layer doesn't appear in any **labels** statement, then it is not attached to a specific layer when output in CIF.

12.5 Calma (GDS II Stream format) layers

Each layer description in the **cifoutput** section may also contain one of the following statements:

gds gdsNumber gdsType calma gdsNumber gdsType Although the format is rarely referred to as "Calma" anymore, the keyword is retained for backwards compatibility with format 27 (and earlier) files.

This statement tells Magic which layer number and data type to use when the **gds** command outputs GDS II Stream format for this defined CIF layer. Both *gdsNumber* and *gdsType* should be positive integers, between 0 and 63. Each CIF layer should have a different *gdsNumber*. If there is no **gds** line for a given CIF layer, then that layer will not be output by the "**gds write**" command. The reverse is not true: every generated output layer must have a defined CIF layer type, even if the foundry only supports GDS format. In such case, the CIF layer name may violate the restrictive 4-character format required by the CIF syntax specification, and may be used to provide a reasonable, human-readable descriptive name of the GDS layer.

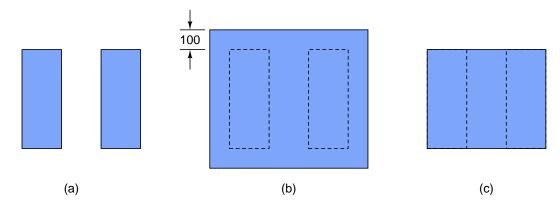


Figure 5: If the operator **grow 100** is applied to the shapes in (a), the merged shape in (b) results. If the operator **shrink 100** is applied to (b), the result is (c). However, if the two original shapes in (a) belong to different cells, and if CIF is generated separately in each cell, the result will be the same as in (a). Magic handles this by outputting additional information in the parent of the subcells to fill in the gap between the shapes.

12.6 Hierarchy

Hierarchical designs make life especially difficult for the CIF generator. The CIF corresponding to a collection of subcells may not necessarily be the same as the sum of the CIF's of the individual cells. For example, if a layer is generated by growing and then shrinking, nearby features from different cells may merge together so that they don't shrink back to their original shapes (see Figure 5). If Magic generates CIF separately for each cell, the interactions between cells will not be reflected properly. The CIF generator attempts to avoid these problems. Although it generates CIF in a hierarchical representation that matches the Magic cell structure, it tries to ensure that the resulting CIF patterns are exactly the same as if the entire Magic design had been flattened into a single cell and then CIF were generated from the flattened design. It does this by looking in each cell for places where subcells are close enough to interact with each other or with paint in the parent. Where this happens, Magic flattens the interaction area and generates CIF for it; then Magic flattens each of the subcells separately and generates CIF for them. Finally, it compares the CIF from the subcells with the CIF from the flattened parent. Where there is a difference, Magic outputs extra CIF in the parent to compensate.

Magic's hierarchical approach only works if the overall CIF for the parent ends up covering at least as much area as the CIFs for the individual components, so all compensation can be done by adding extra CIF to the parent. In mathematical terms, this requires each geometric operation to obey the rule

$$Op(A \cup B) \supseteq Op(A) \cup Op(B)$$

The operations **and**, **or**, **grow**, and **shrink** all obey this rule. Unfortunately, the **and-not**, **bloat**, and **squares** operations do not. For example, if there are two partially-overlapping tiles in different cells, the squares generated from one of the cells may fall in the separations between squares in the other cell, resulting in much larger areas of material than expected. There are two ways around this problem. One way is to use the design rules to prohibit problem situations from arising. This applies mainly to the **squares** operator. Tiles from which squares are made should never be allowed to overlap other such tiles in different cells unless the overlap is exact, so each cell will generate squares in the same place. You can use the **exact_overlap** design rule for this.

The second approach is to leave things up to the designer. When generating CIF, Magic issues warnings where there is less material in the children than the parent. The designer can locate these problems and eliminate the interactions that cause the trouble. Warning: Magic does not check the **squares** operations for hierarchical consistency, so you absolutely must use **exact_overlap** design rule checks! Right now, the **cifoutput** section of the technology is one of the trickiest things in the whole file, particularly since errors here may not show up until your chip comes back and doesn't work. Be extremely careful when writing this part!

Another problem with hierarchical generation is that it can be very slow, especially when there are a number of rules in the cifoutput section with very large grow or shrink distances, such that magic must always expand its area of interest by this amount to be sure of capturing all possible layer interactions. When this "halo" distance becomes larger than the average subcell, much of the design may end up being processed multiple times. Noticeably slow output generation is usually indicative of this problem. It can be alleviated by keeping output rules simple. Note that basic AND and OR operations do not interact between subcells, so that rules made from only these operators will not be processed during subcell interaction generation. Remember that typically, subcell interaction paint will only be generated for layers that have a "grow" operation followed by a "shrink" operation. This common ruleset lets layers that are too closely spaced to be merged together, thus eliminating the need for a spacing rule between the layers. But consider carefully before implementing such a rule. Implementing a DRC spacing rule instead may eliminate a huge amount of output processing. Usually this situation crops up for auto-generated layers such as implants and wells, to prevent magic from auto-generating DRC spacing violations. But again, consider carefully whether it might be better to require the layout engineer to draw the layers instead of attempting to auto-generate them.

12.7 Render statements

At the end of each style in the **cifoutput** section, one may include **render** statements, one per defined CIF/GDS layer. These **render** statements are used by the 3-D drawing window in the OpenGL graphics version of magic, and are also used by the "**cif see**" command to set the style painted. The syntax for the statement is as follows:

cifinput
style lambda=1.0(gen)
scalefactor 100
layer m1 CMF
labels CMF
layer ndiff CSN
and CAA
layer nsd CWN
and CSN
and CAA
layer nfet CPG
and CAA
and CSN
layer ndc CCA
grow 100
and CAA
and CWP
and CSN
and CMF
layer nncont CCA
grow 100
and CAA
and CSN
and CWN
and CMF
calma CAA 1 *
calma CCA 2 *
calma CMF 4 *
calma CPG 7 *
calma CSN 8 *
calma CWN 11 *
calma CWP 12 *
end

Table 10: Part of the **cifinput** section. The order of the layers is important, since each Magic layer overrides the previous ones just as if they were painted by hand.

render cif_layer style_name height thickness

The *cif_layer* is any valid layer name defined in the same **cifoutput** section where the **render** statement occurs. The *style_name* is the name or number of a style in the styles file. The names are the same as used in the **styles** section of the technology file. *height* and *thickness* are effectively dimensionless units and are used for relative placement and scaling of the three-dimensional layout view (such views generally have a greatly expanded z-axis scaling). By default, all layers are given

the same style and a zero height and thickness, so effectively nothing useful can be seen in the 3-D view without a complete set of **render** statements.

13 Cifinput section

In addition to writing CIF, Magic can also read in CIF files using the **:cif read** *file* command. The **cifinput** section of the technology file describes how to convert from CIF mask layers to Magic tile types. In addition, it provides information to the Calma reader to allow it to read in Calma GDS II Stream format files. The **cifinput** section is very similar to the **cifoutput** section. It can contain several styles, with a line of the form

style *name*

used to end the description of the previous style (if any), and start a new CIF input style called *name*. If no initial style name is given, the name **default** is assigned. Each style must have a statement of the form

scalefactor scale [nanometers]

to indicate the output scale relative to Magic units. Without the optional keyword **nanometers**, *scale* describes how many hundredths of a micron correspond to one unit in Magic. With **nanometers** declared, *scale* describes how many nanometers correspond to one unit in Magic.

Like the **cifoutput** section, each style consists of a number of layer descriptions. A layer description contains one or more lines describing a series of geometric operations to be performed on CIF layers. The result of all these operations is painted on a particular Magic layer just as if the user had painted that information by hand. A layer description begins with a statement of the form

layer magicLayer [layers]

In the **layer** statement, *magicLayer* is the Magic layer that will be painted after performing the geometric operations, and *layers* is an optional list of CIF layers. If *layers* is specified, it is the initial value for the layer being built up. If *layers* isn't specified, the layer starts off empty. As in the **cifoutput** section, each line after the *layer* statement gives a geometric operation that is applied to the previous contents of the layer being built in order to generate new contents for the layer. The result of the last geometric operation is painted into the Magic database.

The geometric operations that are allowed in the **cifinput** section are a subset of those permitted in the **cifoutput** section:

or layers and layers and-not layers grow amount shrink amount In these commands the *layers* must all be CIF layers, and the *amounts* are all CIF distances (centimicrons, unless the keyword **nanometers** has been used in the **scalefactor** specification). As with the **cifoutput** section, layers can only be specified in simple comma-separated lists: tildes and slashes are not permitted.

When CIF files are read, all the mask information is read for a cell before performing any of the geometric processing. After the cell has been completely read in, the Magic layers are produced and painted in the order they appear in the technology file. In general, the order that the layers are processed is important since each layer will usually override the previous ones. For example, in the scmos tech file shown in Table 10 the commands for **ndiff** will result in the **ndiff** layer being generated not only where there is only ndiffusion but also where there are ntransistors and ndcontacts. The descriptions for **ntransistor** and **ndcontact** appear later in the section, so those layers will replace the **ndiff** material that was originally painted.

Labels are handled in the cifinput section just like in the cifoutput section. A line of the form

labels layers

means that the current Magic layer is to receive all CIF labels on *layers*. This is actually just an initial layer assignment for the labels. Once a CIF cell has been read in, Magic scans the label list and re-assigns labels if necessary. In the example of Table 10, if a label is attached to the CIF layer CPG then it will be assigned to the Magic layer **poly**. However, the polysilicon may actually be part of a poly-metal contact, which is Magic layer **pcontact**. After all the mask information has been processed, Magic checks the material underneath the layer, and adjusts the label's layer to match that material (**pcontact** in this case). This is the same as what would happen if a designer painted **poly** over an area, attached a label to the material, then painted **pcontact** over the area.

No hierarchical mask processing is done for CIF input. Each cell is read in and its layers are processed independently from all other cells; Magic assumes that there will not be any unpleasant interactions between cells as happens in CIF output (and so far, at least, this seems to be a valid assumption).

If Magic encounters a CIF layer name that doesn't appear in any of the lines for the current CIF input style, it issues a warning message and ignores the information associated with the layer. If you would like Magic to ignore certain layers without issuing any warning messages, insert a line of the form

ignore cifLayers

where *cifLayers* is a comma-separated list of one or more CIF layer names.

Calma layers are specified via **calma** lines, which should appear at the end of the **cifinput** section. They are of the form:

calma cifLayer calmaLayers calmaTypes

The *cifLayer* is one of the CIF types mentioned in the **cifinput** section. Both *calmaLayers* and *calmaTypes* are one or more comma-separated integers between 0 and 63. The interpretation of a **calma** line is that any Calma geometry whose layer is any of the layers in *calmaLayers*, and whose type is any of the types in *calmaTypes*, should be treated as the CIF layer *cifLayer*. Either or both of *calmaLayers* and *calmaTypes* may be the character * instead of a comma-separated list of

integers; this character means *all* layers or types respectively. It is commonly used for *calmaTypes* to indicate that the Calma type of a piece of geometry should be ignored.

Just as for CIF, Magic also issues warnings if it encounters unknown Calma layers while reading Stream files. If there are layers that you'd like Magic to ignore without issuing warnings, assign them to a dummy CIF layer and ignore the CIF layer.

14 Lef section

This section defines a mapping between magic layers and layers that may be found in LEF and DEF format files. Without the section, magic cannot read a LEF or DEF file. The LEF and DEF layer declarations are usually simple and straightforward (as they typically define metal layers only), so often it will suffice to insert a plain vanilla **lef** section into a technology file if one is missing. The **lef** section was introduced in technology file format 28, and is therefore absent from all .tech27 technology files. All of the statements in the **lef** section have the same format:

layer magic-type lefdef-type ... **cut** magic-type lefdef-type ... **route**|**routing** magic-type lefdef-type ... **obstruction** magic-type lefdef-type ... **masterslice** magic-type lefdef-type ... **overlap** magic-type lefdef-type ...

Each statement defines a mapping between a Magic layer type *magic-type* and one or more type names *lefdef-type* (space-separated) that might be encountered in a LEF or DEF file. The different command names all refer to different type classes defined by the LEF/DEF specification. For most purposes, it is only necessary to use the **layer** statement. If the magic type is a contact type, then the **layer** statement is equivalent to specifying **cut**; otherwise, it is equivalent to **route**.

Table 11 is a typical **lef** section for a 5-metal technology, which encompasses the most commonly used layer names found in LEF and DEF files.

15 Mzrouter section

This section defines the layers and contacts available to the Magic maze router, *mzrouter*, and assigns default costs for each type. Default widths and spacings are derived from the **drc** section of the technology file (described below) but can be overridden in this section. Other mzrouter parameters, for example, search rate and width, can also be specified in this section. The syntax and function of the lines in the **mzrouter** section of the technology file are specified in the subsections below. Each set of specifications should be headed by a **style** line. **Routelayer** and **routecontact** specifications should precede references to them.

15.1 Styles

The mzrouter is currently used in two contexts, interactively via the **iroute** command, and as a subroutine to the garouter for stem generation. To permit distinct parameters for these two uses,

lef						
	masterslice	ndiff	diffusion	active		
	masterslice	poly	poly	POLY1	pl	
	routing	m1	m1	metal1	METAL1	METAL_1
	routing	m2	m2	metal2	METAL2	METAL_2
	routing	m3	m3	metal3	METAL3	METAL_3
	routing	m4	m4	metal4	METAL4	METAL_4
	routing	m5	m5	metal5	METAL5	METAL_5
	cut	pc	cont1	pl-m1		
	cut	m2c	vial	cont2	VIA12	m1-m2
	cut	m3c	via2	cont3	VIA23	m2-m3
	cut	m4c	via3	cont4	VIA34	m3-m4
	cut	m5c	via4	cont5	VIA45	m4-m5
	overlap	comment	overlap	OVERLAP		
end						

Table 11: A plain vanilla lef section.

the lines in the **mzrouter** section are grouped into *styles*. The lines pertaining to the irouter should be preceded by

style irouter

and those pertaining to the garouter should be preceded by the specification

style garouter

Other styles can be specified, but are currently not used. Table 12 shows the mzrouter section from the scmos technology.

15.2 Layers

Layer lines define the route-layers available to the maze router in that style. They have the following form:

layer type hCost vCost jogCost hintCost

Here *type* is the name of the tiletype of the layer and hCost, vCost, jogCost and hintCost, are non-negative integers specifying the cost per unit horizontal distance, cost per unit vertical distance, cost per jog, and cost per unit area of deviation from magnets, respectively. Route layers for any given style must lie in distinct planes.

mzrouter					
style	irouter				
layer	m2	32	64	256	1
layer	m1	64	32	256	1
layer	poly	128	128	512	1
contact	m2contact	metal1	metal2	1024	
contact	pcontact	metal1	poly	2056	
notactive	poly	pcontact			
style	garouter				
layer	m2	32	64	256	1
layer	m1	64	32	256	1
contact	m2contact	metal1	metal2	1024	
end					

Table 12: Mzrouter section for the scmos technology.

15.3 Contacts

Contact lines specify the route-contacts available to the mzrouter in the current style. They have the following form:

contact type routeLayer1 routeLayer2 cost

Here *type* is the tiletype of the contact, *routeLayer1* and *routeLayer2* are the two layers connected by the contact, and *cost* is a nonnegative integer specifying the cost per contact.

15.4 Notactive

It maybe desirable to have a layer or contact available to the maze router, but default to off, i.e., not be used by the mzrouter until explicitly made active. Route-types (route-layers or route-contacts) can be made to default to off with the following specification:

notactive *route-type* ... [route-typen]

15.5 Search

The search rate, width, and penalty parameters can be set with a specification of the form:

search rate width penalty

Here *rate* and *width* are positive integers. And *penalty* is a positive rational (it may include a decimal point). See the irouter tutorial for a discussion of these parameters. (Note that **penalty** is a "wizardly" parameter, i.e., it is interactively set and examined via **iroute wizard** not **iroute search**). If no **search** line is given for a style, the overall mzrouter defaults are used.

15.6 Width

Appropriate widths for route-types are normally derived from the **drc** section of the technology file. These can be overridden with width specifications of the following form:

width route-type width

Here width is a positive integer.

15.7 Spacing

Minimum spacings between routing on a route-type and other types are derived from the design rules. These values can be overridden by explicit spacing specifications in the **mzrouter** section. Spacing specifications have the following form:

spacing routetype type1 spacing1 ...[typen spacingn]

Spacing values must be nonnegative integers or **NIL**. The special type **SUBCELL** can be used to specify minimum spacing to unexpanded subcells.

16 Drc section

The design rules used by Magic's design rule checker come entirely from the technology file. We'll look first at two simple kinds of rules, **width** and and **spacing**. Most of the rules in the **drc** section are one or the other of these kinds of rules.

16.1 Width rules

The minimum width of a collection of types, taken together, is expressed by a **width** rule. Such a rule has the form:

width type-list width error

where *type-list* is a set of tile types (see Section 8 for syntax), *width* is an integer, and *error* is a string, enclosed in double quotes, that can be printed by the command **:drc why** if the rule is violated. A width rule requires that all regions containing any types in the set *types* must be wider than *w* in both dimensions. For example, in Table 14, the rule

width nwell 6 "*N-Well width must be at least 6 (MOSIS rule #1.1)*"

means that nwells must be at least 6 units wide whenever they appear. The *type-list* field may contain more than a single type, as in the following rule:

width allDiff 2 " *Diffusion width must be at least 2 (MOSIS rule #2.1)*"

#define	allDiff	ndiff,pdiff,ndc/a,pdc/a,ppcont/a,nncont/a,pfet,nfet,psd,nsd
#define	extPoly	poly,pcontact
#define	extM1	metal1,pcontact/m1,ndc/m1,ppcont/m1,pdc/m1,nncont/m1
#define	extM2	metal2,m2contact/m2

Table 13: Abbreviations for sets of tile types.

width	pwell	6	" P-Well width must be at least 6 (MOSIS rule #1.1)"	
width	nwell	6	"N-Well width must be at least 6 (MOSIS rule #1.1)"	
width	allDiff	2	"Diffusion width must be at least 2 (MOSIS rule #2.1)"	
width	allPoly	2	"Polysilicon width must be at least 2 (MOSIS rule #3.1)"	

Table 14: Some width rules in the **drc** section.

which means that all regions consisting of the types containing any kind of diffusion be at least 2 units wide. Because many of the rules in the **drc** section refer to the same sets of layers, the **#define** facility of the C preprocessor is used to define a number of macros for these sets of layers. Table 13 gives a complete list.

All of the layers named in any one width rule must lie on the same plane. However, if some of the layers are contacts, Magic will substitute a different contact image if the named image isn't on the same plane as the other layers.

16.2 Spacing rules

The second simple kind of design rule is a **spacing** rule. It comes in two flavors: **touching_ok**, and **touching_illegal**, both with the following syntax:

spacing types1 types2 distance flavor error

The first flavor, **touching_ok**, does not prohibit *types1* and *types2* from being immediately adjacent. It merely requires that any type in the set *types1* must be separated by a "Manhattan" distance of at least *distance* units from any type in the set *types2* that is not immediately adjacent to the first type. See Figure 16.2 for an illustration of Manhattan distance for design rules. As an example, consider the metal1 separation rule:

spacing allPoly allPoly 2 touching_ok \ "Polysilicon spacing must be at least 2 (MOSIS rule #3.2)"

This rule is symmetric (*types1* is equal to *types2*), and requires, for example, that a pcontact be separated by at least 2 units from a piece of polysilicon. However, this rule does not prevent the pcontact from touching a piece of poly. In **touching_ok** rules, all of the layers in both *types1* and *types2* must be stored on the same plane (Magic will substitute different contact images if necessary).

TOUCHING_OK SPACING RULES DO NOT WORK FOR VERY LARGE SPACINGS (RELATIVE TO THE TYPES INVOLVED). SEE FIGURE 6 FOR AN EXPLANATION. If the

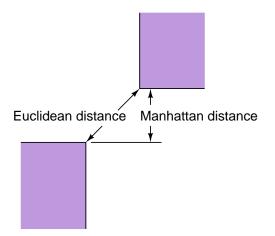


Figure 6: For design rule checking, the Manhattan distance between two horizontally or vertically aligned points is just the normal Euclidean distance. If they are not so aligned, then the Manhattan distance is the length of the longest side of the right triangle forming the diagonal line between the points.

spacing	allPoly	allPoly	2	touching_ok \				
	"Polysilicon spacing must be at least 2 (MOSIS rule #3.2)"							
spacing	pfet	nncont,nnd	3	touching_illegal \				
	" Transistors must be separated from substrate contacts by 3 (MOSIS rule #4.1)"							
spacing	pc	allDiff	1	touching_illegal \				
	"Poly contact must be 1 unit from diffusion (MOSIS rule #5B.6)"							

Table 15: Some spacing rules in the drc section.

spacing to be checked is greater than the width of one of the types involved plus either its selfspacing or spacing to a second involved type, **touching_ok spacing** may not work properly: a violation can be masked by an intervening touching type. In such cases the rule should be written using the **edge4way** construct described below.

The second flavor of spacing rule, **touching_illegal**, disallows adjacency. It is used for rules where *types1* and *types2* can never touch, as in the following:

spacing pc allDiff 1 touching_illegal \

"Poly contact must be 1 unit from diffusion (MOSIS rule #5B.6)"

Pcontacts and any type of diffusion must be at least 1 unit apart; they cannot touch. In **touch-ing_illegal** rules *types1* and *types2* may not have any types in common: it would be rather strange not to permit a type to touch itself. In **touching_illegal** rules, *types1* and *types2* may be spread across multiple planes; Magic will find violations between material on different planes.

6

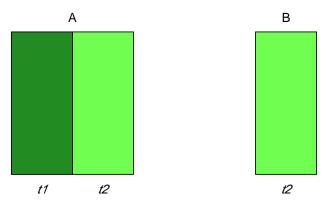


Figure 7: The **touching_ok** rules cancels spacing checks if the material is touching. This means that even distant material won't be checked for spacing. If the rule applied at edge A is a touching_ok rule between material t1 and t2, then no check will be made between the t1 material and the t2 material on the far right side of the diagram. If this check was desired, it could be accomplished in this case by a **edge4way** check from edge B. This would not work in general, though, because that check could also be masked by material of type t2, causing the touching_ok rule to be invoked.

16.3 Wide material spacing rules

Many fabrications processes require a larger distance between layers when the width and length of one of those layers exceeds a certain minimum dimension. For instance, a process might declare that the normal spacing between metall lines is 3 microns. However, if a metall line exceeds a width of 100 microns, then the spacing to other unrelated metall lines must increase to 10 microns. This situation is covered by the **widespacing** rule. The syntax for **widespacing** is as follows:

widespacing types1 wwidth types2 distance flavor error

The **widespacing** rule matches the syntax of **spacing** in all respects except for the addition of the parameter *wwidth*, which declares the minimum width of layers of type(s) *types1* that triggers the rule. So for the example above, the correct **widespacing** rule would be (assuming 1 magic unit = 1 micron):

widespacing allMetal1 100 allMetal1 10 touching_ok \

"Space to wide Metal1 (length and width > 100) must be at least 10"

16.4 Surround rule

The **surround** rule specifies what distance a layer must surround another, and whether the presence of the surrounding material is optional or mandatory. This rule is designed for materials which must *completely* surround another, such as metal around a contact cut or MiM capacitor layer. The syntax is:

surround types1 types2 distance presence error

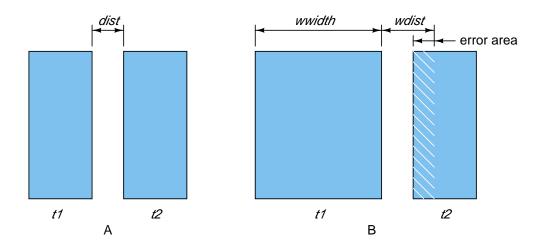


Figure 8: The **widespacing** rule covers situations like that shown above, in which material of type t1 normally must be *dist* units away from type t2 (situation A). However, if both dimensions of material type t1 are larger than or equal to some width *wwidth* (situation B), then the spacing must be increased to *wdist*.

and states that the layers in *types2* must surround the layers in *types1* by an amound *distance* lambda units. The value of *presence* must be one of the keywords **absence_ok** or **absence_illegal**. When *presence* is **absence_illegal**, then types *types2* must always be present when types *types1* are present. When *presence* is **absence_ok**, types *types1* may exist outside of types *types2* without error, but where they coincide, types *types2* must overlap *types1* by the amount *distance*.

16.5 Overhang rule

rule specifies what distance a layer must overhang another at an intersection. This is used, for example, to specify the length of polysilicon end-caps on transistors, which is the distance that the polysilicon gate must extend beyond the defined gate area of the transistor to ensure a correctly operating device. The syntax is:

overhang types1 types2 distance error

and states that layers in *types1* must overhang layers in *types2* by an amount *distance* lambda units. The rule flags the complete absence of types *types1*, but does not prohibit the use of *types1* as a bridge (that is, with types *types2* on either side of *types1*, which will generally be covered by a separate spacing rule, and which may have a different spacing requirement).

16.6 Rectangle-only rule

The **rect_only** rule is used to denote layers that must be rectangular; that is, they cannot bend, or have notches or tabs. Generally, this is used for contacts, so that the CIF output operator **squares** will be guaranteed to generate a correct contact. This is due to magic's corner-stitching tile database, where bends, notches, tabs, and slots will break up an otherwise continuous patch of material into potentially many small tiles, each one of which might be too small to fit a contact cut.

rect_only types error

16.7 Edge rules

The width and spacing rules just described are actually translated by Magic into an underlying, edge-based rule format. This underlying format can handle rules more general than simple widths and spacings, and is accessible to the writer of a technology file via **edge** rules. These rules are applied at boundaries between material of two different types, in any of four directions as shown in Figure 9. The design rule table contains a separate list of rules for each possible combination of materials on the two sides of an edge.

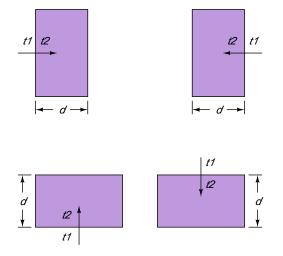


Figure 9: Design rules are applied at the edges between tiles in the same plane. A rule is specified in terms of type t1 and type t2, the materials on either side of the edge. Each rule may be applied in any of four directions, as shown by the arrows. The simplest rules require that only certain mask types can appear within distance d on t2's side of the edge.

In its simplest form, a rule specifies a distance and a set of mask types: only the given types are permitted within that distance on *type2*'s side of the edge. This area is referred to as the *constraint region*. Unfortunately, this simple scheme will miss errors in corner regions, such as the case shown in Figure 10. To eliminate these problems, the full rule format allows the constraint region to be extended past the ends of the edge under some circumstances. See Figure 11 for an illustration of the corner rules and how they work. Table 16 gives a complete description of the information in each design rule.

Edge rules are specified in the technology file using the following syntax:

edge types1 types2 d OKTypes cornerTypes cornerDist error [plane]

Both *types1* and *types2* are type-lists. An edge rule is generated for each pair consisting of a type from *types1* and a type from *types2*. All the types in *types1*, *types2*, and *cornerTypes* must lie on a single plane. See Figure 11 for an example edge rule. It is sometimes useful to specify a null list, i.e., **0**, for *OKTypes* or *CornerTypes*. Null *OKTypes* means no edges between *types1* and

types2 are OK. Null *CornerTypes* means no corner extensions are to be checked (corner extensions are explained below).

Some of the edge rules in Magic have the property that if a rule is violated between two pieces of geometry, the violation can be discovered looking from either piece of geometry toward the other. To capitalize on this, Magic normally applies an edge rule only in two of the four possible directions: bottom-to-top and left-to-right, reducing the work it has to do by a factor of two. Also, the corner extension is only performed to one side of the edge: to the top for a left-to-right rule, and to the left for a bottom-to-top rule. All of the width and spacing rules translate neatly into edge rules.

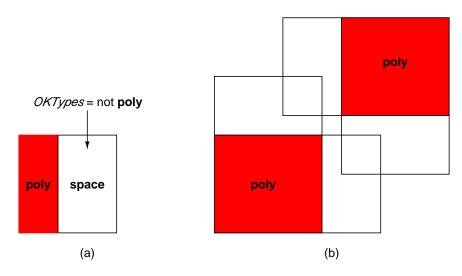
However, you'll probably find it easiest when you're writing edge rules to insist that they be checked in all directions. To do this, write the rule the same way except use the keyword **edge4way** instead of **edge**:

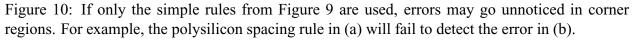
edge4way nfet ndiff 2 ndiff,ndc ndiff 2 \
 " Diffusion must overhang transistor by at least 2"

Not only are **edge4way** rules checked in all four directions, but the corner extension is performed on *both* sides of the edge. For example, when checking a rule from left-to-right, the corner extension is performed both to the top and to the bottom. **Edge4way** rules take twice as much time to check as **edge** rules, so it's to your advantage to use **edge** rules wherever you can.

Normally, an edge rule is checked completely within a single plane: both the edge that triggers the rule and the constraint area to check fall in the same plane. However, the *plane* argument can be specified in an edge rule to force Magic to perform the constraint check on a plane different from the one containing the triggering edge. In this case, *OKTypes* must all be tile types in *plane*. This feature is used, for example, to ensure that polysilicon and diffusion edges don't lie underneath metal2 contacts:

edge4way allPoly ~(allPoly)/active 1 ~m2c/metal2 ~(allPoly)/active 1 \





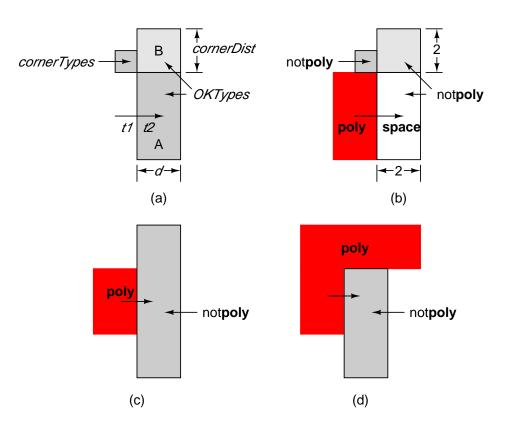


Figure 11: The complete design rule format is illustrated in (a). Whenever an edge has *type1* on its left side and *type2* on its right side, the area A is checked to be sure that only *OKTypes* are present. If the material just above and to the left of the edge is one of *cornerTypes*, then area B is also checked to be sure that it contains only *OKTypes*. A similar corner check is made at the bottom of the edge. Figure (b) shows a polysilicon spacing rule, (c) shows a situation where corner extension is performed on both ends of the edge, and (d) shows a situation where corner extension is made only at the bottom of the edge. If the rule described in (d) were to be written as an **edge** rule, it would look like:

edge poly space 2 ~poly ~poly 2 \
 "Poly-poly separation must be at least 2"

"Via must be on a flat surface (MOSIS rule #8.4,5)" metal2

Magic versions using techfile formats more recent than 28 are generally more clever about determining the correct plane from *OKTypes* when they differ from the triggering types, and the situation is unambiguous (use of "space" in rules tends to introduce ambiguity, since space tiles appear on all planes).

Parameter	Meaning
type1	Material on first side of edge.
type2	Material on second side of edge.
d	Distance to check on second side of edge.
OKTypes	List of layers that are permitted within d units on
	second side of edge. (OKTypes=0 means never
	OK)
cornerTypes	List of layers that cause corner extension. (cor-
	<i>nerTypes</i> =0 means no corner extension)
cornerDist	Amount to extend constraint area when corner-
	<i>Types</i> matches.
plane	Plane on which to check constraint region (de-
	faults to same plane as <i>type1</i> and <i>type2</i> and <i>cor</i> -
	nerTypes).

Table 16: The parts of an edge-based rule.

edge4way	ppcont,ppd	ndiff,ndc,nfet	3	ndiff,ndc,nfet	ndiff,ndc,nfet	3 \
	" Ndiff must	be 3 wide if it abut	s pp	ocont or ppd (M	OSIS rule #??)"	
edge4way	allPoly	~(allPoly)/active	3	~pc/active	~(allPoly)/active	3 \
	" Poly conta	ct must be at least .	3 fre	om other poly (M	10SIS rule #5B.4,5)"	
edge4way	allPoly	~(allPoly)/active	1	~m2c/metal2	~(allPoly)/active	1 \
	" Via must b	e on a flat surface	(MC) SIS rule #8.4,5)	" metal2	

Table 17: Some edge rules in the drc section.

16.8 Subcell Overlap Rules

In order for CIF generation and circuit extraction to work properly, certain kinds of overlaps between subcells must be prohibited. The design-rule checker provides two kinds of rules for restricting overlaps. They are

exact_overlap type-list
no_overlap type-list1 type-list2

In the **exact_overlap** rule, *type-list* indicates one or more tile types. If a cell contains a tile of one of these types and that tile is overlapped by another tile of the same type from a different cell, then the overlap must be exact: the tile in each cell must cover exactly the same area. Abutment between tiles from different cells is considered to be a partial overlap, so it is prohibited too. This rule is used to ensure that the CIF **squares** operator will work correctly, as described in Section 12.6. See Table 18 for the **exact_overlap** rule from the standard scmos technology file.

The **no_overlap** rule makes illegal any overlap between a tile in *type-list1* and a tile in *type-list2*. You should rarely, if ever, need to specify **no_overlap** rules, since Magic automatically prohibits many kinds of overlaps between subcells. After reading the technology file, Magic examines the

exact_overlap	m2c,ndc,pdc,pc,ppcont,nncont
no_overlap	pfet,nfet pfet,nfet

Table 18: Exact_overlap rule in the **drc** section.

paint table and applies the following rule: if two tile types A and B are such that the result of painting A over B is neither A nor B, or the result of painting B over A isn't the same as the result of painting A over B, then A and B are not allowed to overlap. Such overlaps are prohibited because they change the structure of the circuit. Overlaps are supposed only to connect things without making structural changes. Thus, for example, poly can overlap pcontact without violating the above rules, but poly may not overlap diffusion because the result is efet, which is neither poly nor diffusion. The only **no_overlap** rules you should need to specify are rules to keep transistors from overlapping other transistors of the same type.

16.9 Background checker step size

Magic's background design-rule checker breaks large cells up into smaller pieces, checking each piece independently. For very large designs, the number of pieces can get to be enormous. If designs are large but sparse, the performance of the design-rule checker can be improved tremendously by telling it to use a larger step size for breaking up cells. This is done as follows:

stepsize stepsize

which causes each cell to be processed in square pieces of at most *stepsize* by *stepsize* units. It is generally a good idea to pick a large *stepsize*, but one that is small enough so each piece will contain no more than 100 to 1000 rectangles.

Note that the distances declared in the DRC section are used to determine the "halo" of possible interactions around a tile edge. Magic must consider all paint in all cells simultaneously; thus for each edge in the design, magic must flatten the hierarchy around it to a distance equal to the interaction halo. Clearly this has a huge impact on processing time. Because the DRC is interactive, the performance hit can be noticeable to downright irritating. Often this performance hit can be greatly reduced by removing rules with large distance measures, such as rules involving distances to pads, and widespacing rules. If this is a problem, consider using one technology file for layout, and one which can be used "offline" to do a slow, non-interactive DRC check for pad and widespacing rules on an entire project layout.

17 Extract section

The **extract** section of a technology file contains the parameters used by Magic's circuit extractor. Each line in this section begins with a keyword that determines the interpretation of the remainder of the line. Table 19 gives an example **extract** section.

This section is like the **cifinput** and **cifoutput** sections in that it supports multiple extraction styles. Each style is preceded by a line of the form

extract	
style	lambda=0.7
lambda	70
step	100
sidehalo	4
resist	poly,pfet,nfet 60000
resist	pc/a 50000
resist	pdiff,ppd 120000
resist	ndiff,nnd 120000
resist	m2contact/m1 1200
resist	metal1 200
resist	metal2,pad/m1 60
resist	ppc/a,pdc/a 100000
resist	nnc/a,ndc/a 100000
resist	nwell,pwell 3000000
	1
areacap	poly 33
areacap	metall 17
areacap	metal2,pad/m1 11
areacap	ndiff,nsd 350
areacap	pdiff,psd 200
areacap	ndc/a,nsc/a 367
areacap	pdc/a,psc/a 217
areacap	pcontact/a 50
perimc	allMetal1 space 56
perime	allMetal2 space 55
perme	
overlap	metal1 pdiff,ndiff,psd,nsd 33
overlap	metal2 pdiff,ndiff,psd,nsd 17 metal1
overlap	metal1 poly 33
overlap	metal2 poly 17 metal1
overlap	metal2 metal1 33
Ĩ	
sideoverlap	allMetal1 space allDiff 64
sideoverlap	allMetal2 space allDiff 60
sideoverlap	allMetal1 space poly 64
sideoverlap	allMetal2 space poly 60
sideoverlap	allMetal2 space allMetal1 70
fat	
fet	pfet pdiff,pdc/a 2 pfet Vdd! nwell 0 0
fet	nfet ndiff,ndc/a 2 nfet GND! pwell 0 0
end	

Table 19: Extract section.

style stylename

All subsequent lines up to the next **style** line or the end of the section are interpreted as belonging to extraction style *stylename*. If there is no initial **style** line, the first style will be named "default".

The keywords **areacap**, **perimcap**, and **resist** define the capacitance to substrate and the sheet resistivity of each of the Magic layers in a layout. All capacitances that appear in the **extract** section are specified as an integral number of attofarads (per unit area or perimeter), and all resistances as an integral number of milliohms per square.

The **areacap** keyword is followed by a list of types and a capacitance to substrate, as follows:

areacap types C

Each of the types listed in *types* has a capacitance to substrate of *C* attofarads per square lambda. Each type can appear in at most one **areacap** line. If a type does not appear in any **areacap** line, it is considered to have zero capacitance to substrate per unit area. Since most analysis tools compute transistor gate capacitance directly from the area of the transistor's gate, Magic should produce node capacitances that do not include gate capacitances. To ensure this, all transistors should have zero **areacap** values.

The **perimcap** keyword is followed by two type-lists and a capacitance to substrate, as follows:

perimcap intypes outtypes C

Each edge that has one of the types in *intypes* on its inside, and one of the types in *outtypes* on its outside, has a capacitance to substrate of *C* attofarads per lambda. This can also be used as an approximation of the effects due to the sidewalls of diffused areas. As for **areacap**, each unique combination of an *intype* and an *outtype* may appear at most once in a **perimcap** line. Also as for **areacap**, if a combination of *intype* and *outtype* does not appear in any **perimcap** line, its perimeter capacitance per unit length is zero.

The **resist** keyword is followed by a type-list and a resistance as follows:

resist types R

The sheet resistivity of each of the types in *types* is *R* milliohms per square.

Each **resist** line in fact defines a "resistance class". When the extractor outputs the area and perimeter of nodes in the **.ext** file, it does so for each resistance class. Normally, each resistance class consists of all types with the same resistance. However, if you wish to obtain the perimeter and area of each type separately in the **.ext** file, you should make each into its own resistance class by using a separate **resist** line for each type.

In addition to sheet resistivities, there are two other ways of specifying resistances. Neither is used by the normal Magic extractor, but both are used by the resistance extractor. Contacts have a resistance that is inversely proportional to the number of via holes in the contact, which is proportional (albeit with quantization) to the area of the contact. The **contact** keyword allows the resistance for a single via hole to be specified:

> **contact** *types size R* **contact** *types size border separation R*

where *types* is a comma-separated list of types, *size* is in lambda, and *R* is in milliohms. *Size* is interpreted as a hole-size quantum; the number of holes in a contact is equal to its width divided by *size* times its length divided by *size*, with both quotients rounded down to the nearest integer. The resistance of a contact is *R* divided by the number of holes.

Note that the *size* alone may not compute the same number of contact cuts as would be generated by the *cifoutput* command, since it has no understaning of border and separation, and therefore may compute an incorrect contact resistance. To avoid this problem, the second form provides a way to give values for *border* and *separation*, again in units of lambda. There is no automatic check to guarantee that the extract and cifoutput sections agree on the number of contact cuts for a given contact area.

Transistors also have resistance information associated with them. However, a transistor's resistance may vary depending on a number of variables, so a single parameter is generally insufficient to describe it. The **fetresist** line allows sheet resistivities to be given for a variety of different configurations:

fetresist fettypes region R

where *fettypes* is a comma-separated list of transistor types (as defined in **fet** lines below), *region* is a string used to distinguish between resistance values for a fet if more than one is provided (the special *region* value of "**linear**" is required for the resistance extractor), and *R* is the on-resistance of the transistor in ohms per square (*not* milliohms; there would otherwise be too many zeroes).

Magic also extracts internodal coupling capacitances, as illustrated in Figure 12. The keywords **overlap**, **sidewall**, **sideoverlap**, and **sidehalo** provide the parameters needed to do this.

Overlap capacitance is between pairs of tile types, and is described by the **overlap** keyword as follows:

overlap toptypes bottomtypes cap [shieldtypes]

where *toptypes*, *bottomtypes*, and optionally *shieldtypes* are type-lists and *cap* is a capacitance in attofarads per square lambda. The extractor searches for tiles whose types are in *toptypes* that overlap tiles whose types are in *bottomtypes*, and that belong to different electrical nodes. (The planes of *toptypes* and *bottomtypes* must be disjoint). When such an overlap is found, the capacitance to substrate of the node of the tile in *toptypes* is deducted for the area of the overlap, and replaced by a capacitance to the node of the tile in *bottomtypes*.

If *shieldtypes* are specified, overlaps between *toptypes* and *bottomtypes* that also overlap a type in *shieldtypes* are not counted. The types in *shieldtypes* must appear on a different plane (or planes) than any of the types in *toptypes* or *bottomtypes*.

Parallel wire capacitance is between pairs of edges, and is described by the sidewall keyword:

sidewall intypes outtypes neartypes fartypes cap

where *intypes*, *outtypes*, *neartypes*, and *fartypes* are all type-lists, described in Figure 13. *Cap* is half the capacitance in attofarads per lambda when the edges are 1 lambda apart. Parallel wire coupling capacitance is computed as being inversely proportional to the distance between two edges: at 2 lambda separation, it is equal to the value *cap*; at 4 lambda separation, it is half of

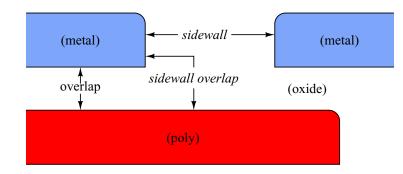


Figure 12: Magic extracts three kinds of internodal coupling capacitance. This figure is a side view of a set of masks that shows all three kinds of capacitance. *Overlap* capacitance is parallel-plate capacitance between two different kinds of material when they overlap. *Parallel wire* capacitance is fringing-field capacitance between the parallel vertical edges of two pieces of material. *Sidewall overlap* capacitance is fringing-field capacitance between the vertical edge of one piece of material and the horizontal surface of another piece of material that overlaps the vertical edge.

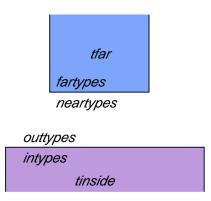


Figure 13: Parallel wire capacitance is between pairs of edges. The capacitance applies between the tiles *tinside* and *tfar* above, where *tinside*'s type is one of *intypes*, and *tfar*'s type is one of *fartypes*.

cap. This approximation is not very good, in that it tends to overestimate the coupling capacitance between wires that are farther apart.

To reduce the amount of searching done by Magic, there is a threshold distance beyond which the effects of parallel wire coupling capacitance are ignored. This is set as follows:

sidehalo distance

where *distance* is the maximum distance between two edges at which Magic considers them to have parallel wire coupling capacitance. If this number is not set explicitly in the technology file, it defaults to 0, with the result that no parallel wire coupling capacitance is computed.

Sidewall overlap capacitance is between material on the inside of an edge and overlapping material of a different type. It is described by the **sideoverlap** keyword:

sideoverlap intypes outtypes ovtypes cap

where *intypes*, *outtypes*, and *ovtypes* are type-lists and *cap* is capacitance in attofarads per lambda. This is the capacitance associated with an edge with a type in *intypes* on its inside and a type in *outtypes* on its outside, that overlaps a tile whose type is in *ovtypes*. See Figure 12.

Devices are represented in Magic by explicit tile types. The extraction of a device id stermined by the declared device type and the information about types which comprise the various independent *terminals* of the device.

device mosfet model gate_types sd_types subs_types subs_node_name \
 [perim_cap [area_cap]]
device capacitor model top_types bottom_types [perim_cap] area_cap
device resistor model resist_types term_types
device bjt model base_types emitter_types collector_types
device diode model pos_types neg_types
device subcircuit model gate_types [term_types [subs_types]]
device rsubcircuit model id_types term_types

Arguments are as follows:

- *model* The SPICE model name of the device. In the case of a subcircuit, it is the subcircuit name. For resistor and capacitor devices for which a simple, unmodeled device type is needed, the *model* can be the keyword **None**.
- *gate_types* Layer types that form the gate region of a MOSFET transistor.
- *sd_types* Layer types that form the source and drain regions of a MOSFET transistor. Currently there is no way to specify a device with asymmetric source and drain.
- *subs_types* Layer types that form the bulk (well or substrate) region under the device. This can be the keyword *None* for a device such as an nFET that has no identifiable substrate layer type ("space" cannot be used as a layer type here).
- *top_types* Layer types that form the top plate of a capacitor.
- *bottom_types* Layer types that form the bottom plate of a capacitor.
- *resist_types* Layer types that represent the primary characterized resistive portion of a resistor device.
- *term_types* Layer types that represent the ends of a resistor. Normally this is a contact type, but in the case of silicide block or high-resistance implants, it may be normal salicided polysilicon or diffusion.
- *base_types* Layer types that represent the base region of a bipolar junction transistor.
- *emitter_types* Layer types that represent the emitter region of a bipolar junction transistor.
- *collector_types* Layer types that represent the collector region of a bipolar junction transistor.
- *pos_types* Layer types that represent the positive (anode) terminal of a diode or P-N junction.

- *neg_types* Layer types that represent the negative (cathode) terminal of a diode or P-N junction.
- *id_types* Identifier layers that identify a specific resistor type.
- *subs_node_name* The default name of a substrate node in cases where a 4-terminal MOSFET device is missing an identifiable bulk terminal, or when the *subs_type* is the keyword **None**.
- perim_cap A value for perimeter capacitance in units of attoFarads per lambda
- area_cap A value for area capacitance in units of attoFarads per lambda squared.

The *subs_node_name* can be a Tcl variable name (beginning with "\$") in the Tcl-based version of magic. Thus, instead of hard-coding a global net name into the general-purpose, project-independent technology file, the technology file can contain a default global power and ground net variable, normally **\$VDD** and **\$VSS**. Each project should then set these variables (in the .magicrc file, for example) to the correct value for the project's default global power and ground networks.

SPICE has two formats for resistors and capacitors: one uses a model, and the other does not. The model implies a semiconductor resistor or capacitor, and takes a length and width value. The resistivity or capacitance per unit area of the devices is assumed to be declared in the model, so these values are not generated as part of the SPICE netlist output.

Magic technology file formats 27 and earlier only understood one device type, the FET transistor. The extraction of a fet (with gate, sources, and drains) from a collection of transistor tiles is governed by the information in a **fet** line. This keyword and syntax is retained for backward compatibility. This line has the following format:

fet types dtypes min-nterms name snode [stypes]gscap gccap

Types is a list of those tiletypes that make up this type of transistor. Normally, there will be only one type in this list, since Magic usually represents each type of transistor with a different tiletype.

Dtypes is a list of those tiletypes that connect to the diffusion terminals of the fet. Each transistor of this type must have at least *min-nterms* distinct diffusion terminals; otherwise, the extractor will generate an error message. For example, an **efet** in the scmos technology must have a source and drain in addition to its gate; *min-nterms* for this type of fet is 2. The tiletypes connecting to the gate of the fet are the same as those specified in the **connect** section as connecting to the fet tiletype itself.

Name is a string used to identify this type of transistor to simulation programs.

The substrate terminal of a transistor is determined in one of two ways. If *stypes* (a commaseparated list of tile types) is given, and a particular transistor overlaps one of those types, the substrate terminal will be connected to the node of the overlapped material. Otherwise, the substrate terminal will be connected to the node with the global name of *snode* (which *must* be a global name, i.e., end in an exclamation point).

Gscap is the capacitance between the transistor's gate and its diffusion terminals, in attofarads per lambda. Finally, *gccap* is the capacitance between the gate and the channel, in attofarads per square lambda. Currently, *gscap* and *gccap* are unused by the extractor.

In technology format 27 files, devices such as resistors, capacitors, and bipolar junction transistors could be extracted by treating them like FETs, using a "fet" line in the extract file, and assigning the terminal classes (somewhat arbitrarily) to the FET terminal classes gate, source/drain, and bulk. Resistors are rather cumbersome using this method, because the "gate" terminal maps to nothing physical, and a dummy layer must be drawn. The "ext2spice" command generates an "M" spice record for all devices declared with a fet line, so an output SPICE deck must be postprocessed to produce the correct SPICE devices for simulation. One important other difference between the older form and the newer is the ability of the "device" records to handle devices with bends or other irregular geometry, including annular (ring-shaped) FETs.

Often the units in the extracted circuit for a cell will always be multiples of certain basic units larger than centimicrons for distance, attofarads for capacitance, or milliohms for resistance. To allow larger units to be used in the **.ext** file for this technology, thereby reducing the file's size, the **extract** section may specify a scale for any of the three units, as follows:

cscale *c* lambda *l* rscale *r*

In the above, c is the number of attofarads per unit capacitance appearing in the **.ext** files, l is the number of centimicrons per unit length, and r is the number of milliohms per unit resistance. All three must be integers; r should divide evenly all the resistance-per-square values specified as part of **resist** lines, and c should divide evenly all the capacitance-per-unit values.

Magic's extractor breaks up large cells into chunks for hierarchical extraction, to avoid having to process too much of a cell all at once and possibly run out of memory. The size of these chunks is determined by the **step** keyword:

step step

This specifies that chunks of *step* units by *step* units will be processed during hierarchical extraction. The default is **100** units. Be careful about changing *step*; if it is too small then the overhead of hierarchical processing will increase, and if it is too large then more area will be processed during hierarchical extraction than necessary. It should rarely be necessary to change *step* unless the minimum feature size changes dramatically; if so, a value of about 50 times the minimum feature size appears to work fairly well.

Magic has the capability to generate a geometry-only extraction of a network, useful for 3-D simulations of electric fields necessary to rigorously determine inductance and capacitance. When this feature is used, it is necessary for the field-equation solver to know the vertical stackup of the layout. The extract section takes care of this by allowing each magic layer to be given a definition of height and thickness of the fabricated layer type:

height layers height thickness

where *layers* is a comma-separated list of magic layers sharing the same height and thickness, and *height* and *thickness* are floating-point numbers giving the height of the bottom of the layer above the substrate, and the thickness of the layer, respectively, in units of lambda.

18 Wiring section

The **wiring** section provides information used by the **:wire switch** command to generate contacts. See Table 20 for the **wiring** section from the scmos technology file. Each line in the section has the syntax

contact type minSize layer1 surround1 layer2 surround2

Type is the name of a contact layer, and *layer1* and *layer2* are the two wiring layers that it connects. *MinSize* is the minimum size of contacts of this type. If *Surround1* is non-zero, then additional material of type *layer1* will be painted for *surround1* units around contacts of *type*. If *surround2* is non-zero, it indicates an overlap distance for *layer2*.

wiring						
contact	pdcontact	4	metal1	0	pdiff	0
contact	ndcontact	4	metal1	0	ndiff	0
contact	pcontact	4	metal1	0	poly	0
contact	m2contact	4	metal1	0	metal2	0
end						

Table 20: Wiring section

During **:wire switch** commands, Magic scans the wiring information to find a contact whose *layer1* and *layer2* correspond to the previous and desired new wiring materials (or vice versa). If a match is found, a contact is generated according to *type*, *minSize*, *surround1*, and *surround2*.

19 Router section

The **router** section of a technology file provides information used to guide the automatic routing tools. The section contains four lines. See Table 21 for an example **router** section.

router						
layer1	metal1	3	allMetal1	3		
layer2	metal2	3	allMetal2	4	allPoly,allDiff	1
contacts	m2contact	4				
gridspacing	8					
end						

Table 21: Router section

The first two lines have the keywords layer1 and layer2 and the following format:

layer1 wireType wireWidth type-list distance type-list distance ...

They define the two layers used for routing. After the **layer1** or **layer2** keyword are two fields giving the name of the material to be used for routing that layer and the width to use for its wires. The remaining fields are used by Magic to avoid routing over existing material in the channels. Each pair of fields contains a list of types and a distance. The distance indicates how far away the given types must be from routing on that layer. Layer1 and layer2 are not symmetrical: wherever possible, Magic will try to route on layer1 in preference to layer2. Thus, in a single-metal process, metal should always be used for layer1.

The third line provides information about contacts. It has the format

contacts contactType size [surround1 surround2]

The tile type *contactType* will be used to make contacts between layer1 and layer2. Contacts will be *size* units square. In order to avoid placing contacts too close to hand-routed material, Magic assumes that both the layer1 and layer2 rules will apply to contacts. If *surround1* and *surround2* are present, they specify overlap distances around contacts for layer1 and layer2: additional layer1 material will be painted for *surround1* units around each contact, and additional layer2 material will be painted for *surround2* units around contacts.

The last line of the **routing** section indicates the size of the grid on which to route. It has the format

gridspacing distance

The *distance* must be chosen large enough that contacts and/or wires on adjacent grid lines will not generate any design rule violations.

20 Plowing section

The **plowing** section of a technology file identifies those types of tiles whose sizes and shapes should not be changed as a result of plowing. Typically, these types will be transistors and buried contacts. The section currently contains three kinds of lines:

fixed types covered types drag types

where *types* is a type-list. Table 22 gives this section for the scmos technology file.

plowing	
fixed	pfet,nfet,glass,pad
covered	pfet,nfet
drag	pfet,nfet
end	

Table 22: Plowing section

In a **fixed** line, each of *types* is considered to be fixed-size; regions consisting of tiles of these types are not deformed by plowing. Contact types are always considered to be fixed-size, so need not be included in *types*.

In a **covered** line, each of *types* will remain "covered" by plowing. If a face of a covered type is covered with a given type before plowing, it will remain so afterwards. For example, if a face of a transistor is covered by diffusion, the diffusion won't be allowed to slide along the transistor and expose the channel to empty space. Usually, you should make all fixed-width types covered as well, except for contacts.

In a **drag** line, whenever material of a type in *types* moves, it will drag with it any minimumwidth material on its trailing side. This can be used, for example, to insure that when a transistor moves, the poly-overlap forming its gate gets dragged along in its entirety, instead of becoming elongated.

21 Plot section

The **plot** section of the technology file contains information used by Magic to generate hardcopy plots of layouts. Plots can be generated in different styles, which correspond to different printing mechanisms. For each style of printing, there is a separate subsection within the **plot** section. Each subsection is preceded by a line of the form

style styleName

Magic version 6.5 and earlier supported **gremlin**, **versatec**, and **colorversatec** styles. As these are thoroughly obsolete, versions 7 and above instead implement two formats **postscript** and **pnm**. Generally, the **pnm** format is best for printouts of entire chips, and the **postscript** format is best for small cells. The PostScript output includes labels, whereas the PNM output does not. The PostScript output is vector-drawn with stipple fills, whereas the PNM output is pixel-drawn, with antialiasing. Small areas of layout tend to look artificially pixellated in the PNM format, while large areas look almost photographic. The PostScript output is a perfect rendering of the Magic layout, but the files become very large and take long spans of time to render for large areas of layout.

The **postscript** style requires three separate sections. The first section defines the stipple patterns used:

index pattern-bytes...

The *index* values are arbitrary but must be a positive integer and must be unique to each line. The indices will be referenced in the third section. The *pattern-bytes* are always exactly 8 sets of 8-digit hexidecimal numbers (4 bytes) representing a total of 16 bits by 16 lines of pattern data. If a solid color is intended, then it is necessary to declare a stipple pattern of all ones. The actual PostScript output will implement a solid color, not a stipple pattern, for considerably faster rendering.

The second section defines the colors used in standard printer CMYK notation (Cyan, Magenta, Yellow, blacK):

index CMYK

plot							
style	postscript						
	5	FFFFFFFF FFFFFFFFFFFFFFFFF	FF FFFFFFFF				
	7	18181818 30303030 60606060 C0C0C0C0					
	9	18181818 3C3C3C3C 3C3C3C3					
	10	F0F0F0F0 60606060 06060606					
	13	0000000 0000000 33333333					
	15	000000000000000000000000000000000000000					
	1	47 95 111 0					
	9	223 47 223 0					
	10	0 255 255 0					
	12	191 127 0 0					
	13	95 223 63 0					
	14	0 0 0 255					
	16	111 151 244 0					
	17	23 175 183 0					
	17	25 175 105 0					
	pc,ndc,pdc,	psc,nsc	14 X				
	m2c		14 B				
	m2c		14 13				
	m2,m2c		13 10				
		,nsc,pc,m1,m2c	12 9				
	poly,pc	,,p •,,	10 5				
	nfet		97				
	nfet		16 5				
	pfet		17				
	pfet		17 5				
	pdiff,pdc		15				
	ndiff,ndc		95				
	nunn,nue		, ,				
style	pnm						
ĩ	draw	metal1					
	draw	metal2					
	draw	polysilicon					
	draw	ndiffusion					
	draw	pdiffusion					
	draw	ntransistor					
	draw	ptransistor					
	map	psubstratepdiff pdiffusion					
	map	nsubstratendiff ndiffusion					
	map	polycontact polysilicon metal1					
	map	m2contact metal1 metal2					
	map	ndcontact ndiffusion metal1					
	map	pdcontact pdiffusion metal1					
end	P	r					
viiu							

Table 23: Sample **plot** section (for an SCMOS process). PostScript stipple patterns have been truncated due to space limitations.

Like the first section, each *index* must be a unique positive integer, and the color values each range from 0 to 255.

The third section assigns colors and stipple patterns to each style:

type-list color-index stipple-index |**X**|**B**

The *type-list* is a comma-separated list of magic layer types that collectively use the same color and style. The *color-index* refers to one of the colors defined in the second section, and the *stipple-index* refers to one of the stipple patterns defined in the first section. In addition to the stipple pattern indices, two characters are recognized: **B** declares that a border will be drawn around the layer boundary, and **X** declares that the layout boundary will be printed over with a cross in the same manner as contact areas are drawn in the Magic layout.

To get a proper PostScript plot, it is necessary to have a properly defined **plot postscript** section in the technology file. Without such a defined set, the **plot postscript** command will generate blank output.

The **pnm** style declarations are as follows:

draw *magic-type* **map** *magic-type draw-type*...

where both *magic-type* and *draw-type* represent a magic layer name. The **draw** command states that a specific magic type will be output exactly as drawn on the layout. The **map** statement declares that a specific magic type will be drawn as being composed of other layers declared as **draw** types. The colors of the **draw** types will be blended to generate the mapped layer color. Colors are defined by the style set used for layout and defined in the **styles** section of the technology file. Stipple patterns, borders, and cross-hatches used by those styles are ignored. When multiple styles are used for a layer type, the PNM output blends the base color of each of those styles. Thus, contact areas by default tend to show up completely black, as the "X" pattern is usually defined as black, and black blended with other colors remains black. This is why the above example redefines all of the contact types as mapped type blends. Contact cuts are not represented, which is generally desired if the plot being made represents a large area of layout.

Unlike the PostScript section, the PNM plot section does *not* have to be declared. Magic will set up a default style for PNM plots that matches (more or less) the colors of the layout as specified by the **styles** section of the technology file. The **plot pnm** section can be used to tweak this default setup. Normally this is not necessary. The default setup is helpful in that it allows the **plot pnm** command to be used with all technology files, including those written before the *plot pnm* command option was implemented.

22 Conditionals, File Inclusions, and Macro Definitions

The "raw" technology files in the **scmos** subdirectory of the Magic distribution were written for a C preprocessor and cannot be read directly by Magic. The C preprocessor must first be used to eliminate comments and expand macros in a technology file before it gets installed, which is done during the "**make install**" step when compiling and installing Magic from source. Macro definitions can be made with the preprocessor **#define** statement, and "conditional compilation" can be specified using **#ifdef**. Also, the technology file can be split into parts using the **#include** statement to read in different parts of the files. However, this has for the most part proven to be a poor method for maintaining technology files. End-users often end up making modifications to the technology files for one purpose or another. They should not need to be making changes to the source code distribution, they often do not have write access to the source distribution, and furthermore, the elimination of comments and macros from the file makes the actual technology file used difficult to read and understand.

Technology file formats more recent that 27 include several built-in mechanisms that take the place of preprocessor statements, and allow the technology file source to be directly edited without the need to re-process. This includes the **include** statement, which may be used anywhere in the technology file, the **alias** statement in the **types** section, and the **variant** statement, which may be used in the **cifoutput**, **cifinput**, or **extract** sections. The **alias** statements appear in the **types** section, covered above. The **include** statement may appear anywhere in the file, and takes the form

include filename

Assuming that the included files exist in the search path Magic uses for finding system files (see command **path sys**), then no absolute path needs to be speficied for *filename*. Note that the file contents will be included verbatim; section names and **end** statements that appear in the included file should not exist in the file that includes it, and vice versa.

The most common use of "#ifdef" preprocessor statements in the default "scmos" technology is to selectively define different cifoutput, cifinput, and extract files for process variants. The result is that these sections become quite large and repeat many definitions that are common to all process variations. Technology file format 30 defines the **variants** option to the **style** statement for all three sections **cifinput**, **cifoutput**, and **extract**. This statement option takes the form:

style stylename variants variantname,...

where *stylename* is a base name used for all variants, and one of the comma-separated list of *variantnames* is a suffix appended to the *stylename* to get the actual name as it would be used in, for example, a **cif ostyle** command. For example, the statement

style scmos0.18 variants (p),(c),(pc),()

defines four similar styles named **scmos0.18(p)**, **scmos0.18(c)**, **scmos0.18(pc)**, and **scmos0.18(**). All of the variants are assumed to be minor variations on the base style. Within each style description, statements may apply to a single variant, a group of variants, or all variants. After the **style** statement has been processed, all following lines are assumed to refer to all variants of the base style until a **variant** statment is encountered. This statement takes the form:

variant variantname,...

to refer to one or more variants in a comma-separated list. All lines following the **variant** statement will apply only to the specific process variants in the list, until another **variant** statement is encountered. The special character "*" can be used as a shorthand notation for specifying all process variants:

variant *